

From Atoms to Devices: Designing Materials for Future Devices

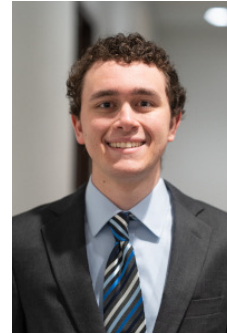
Sanghamitra Neogi

Assistant Professor

Ann and H.J. Smead Aerospace Engineering Sciences
Materials Science and Engineering Program (Program Faculty)
University of Colorado Boulder, Boulder, CO, USA

**Bridging scales: At the crossroads among renormalisation group,
multi-scale modelling, and deep learning, 15 April 2024 — 19 April 2024**

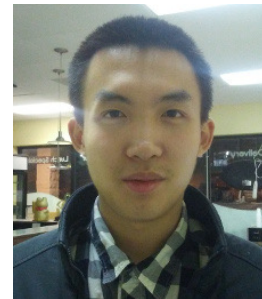
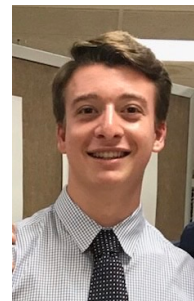
Thank you!



Postdoc
and grad
student
alumni



Undergrad
student alumni



Thank you!

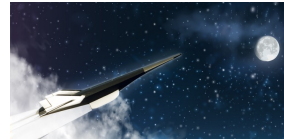


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NATIONAL LABORATORY
Center for Nanoscale Materials

 University of Colorado **Boulder**

Research Computing
OFFICE OF INFORMATION TECHNOLOGY



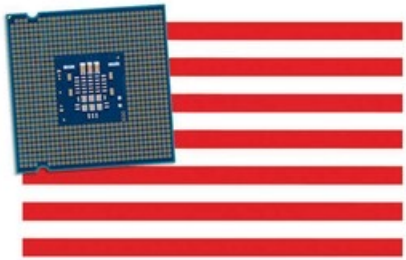
From Atoms to Devices: Microchips

“the most complex piece of machinery
ever assembled by humans.”

NEW YORK TIMES BESTSELLER

"Pulse quickening. If any book can make general audiences grok the Silicon Age—and finally recognize how it rivals the Atomic Age for drama and import—*Chip War* is it." —*THE NEW YORK TIMES*

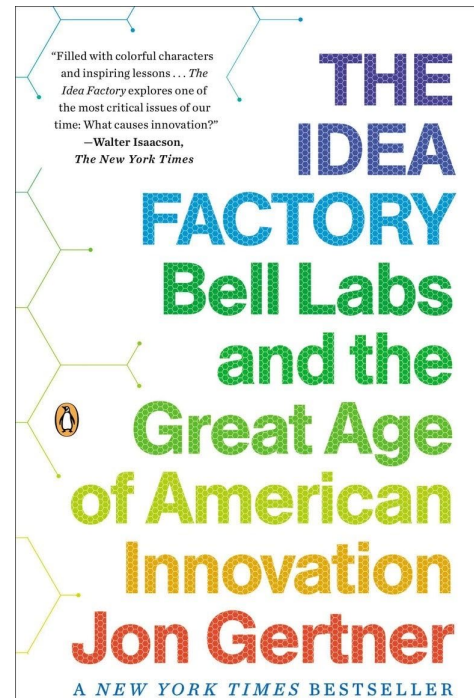
CHIP WAR

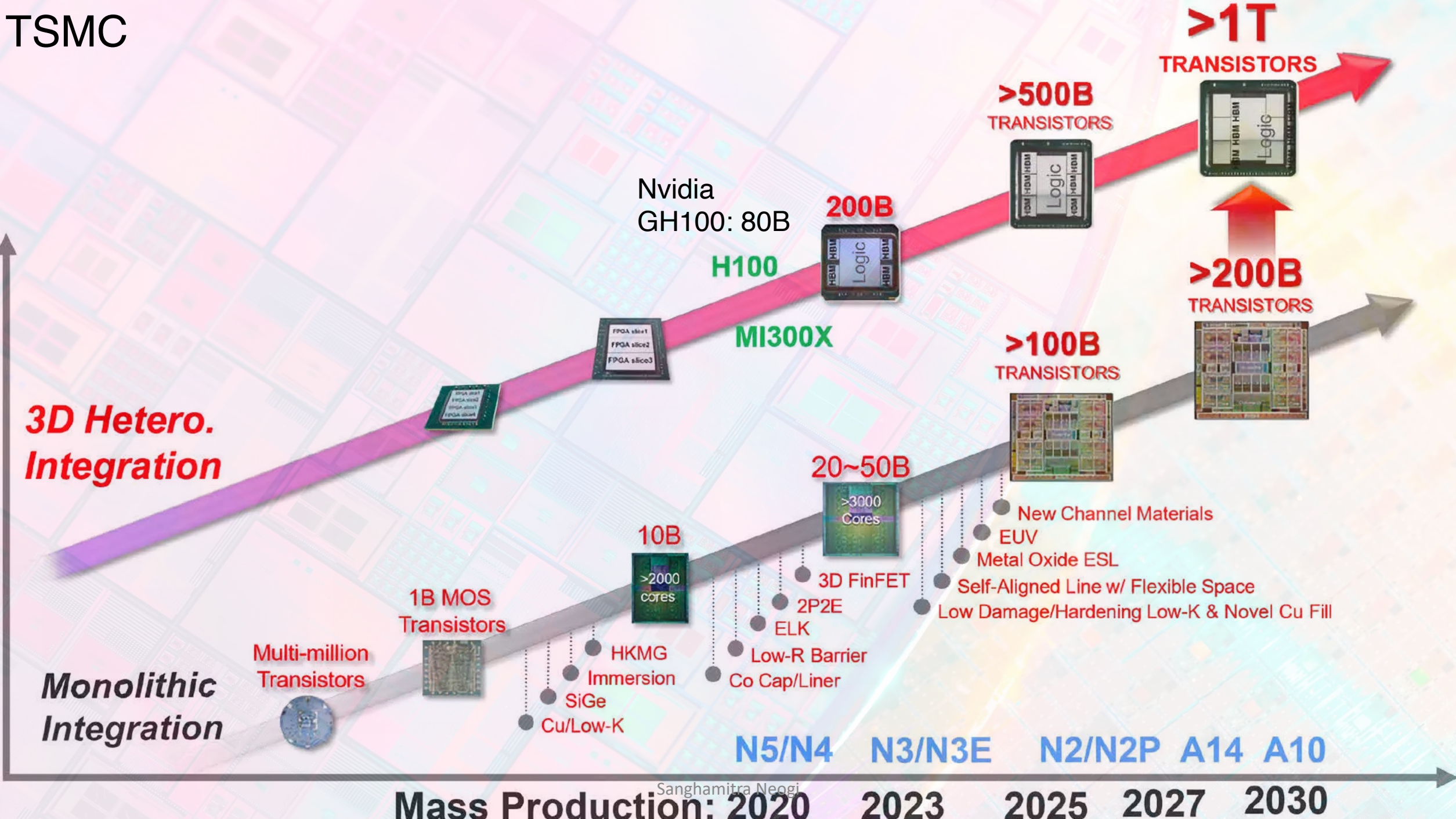


THE FIGHT FOR THE WORLD'S
MOST CRITICAL TECHNOLOGY

CHRIS MILLER

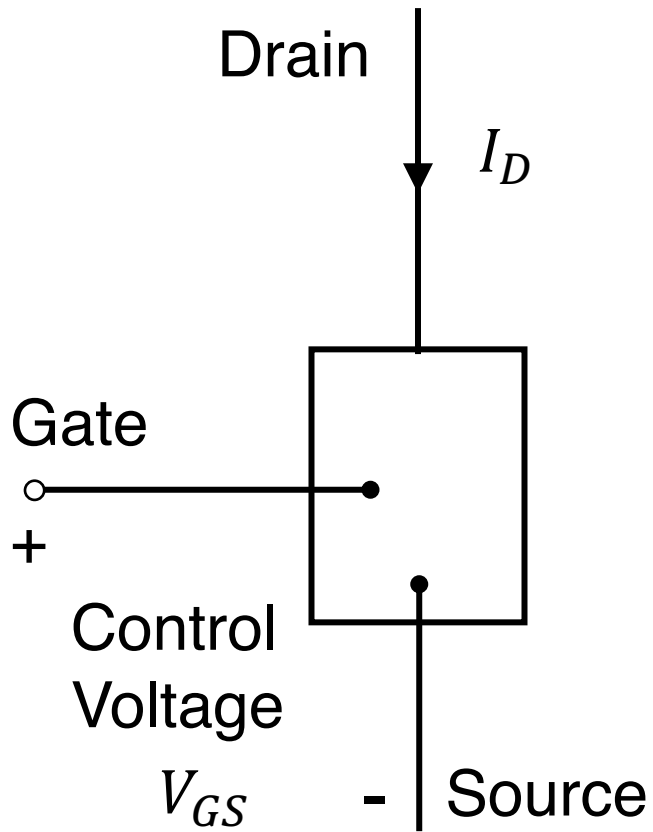
“Microchips are the new oil.”



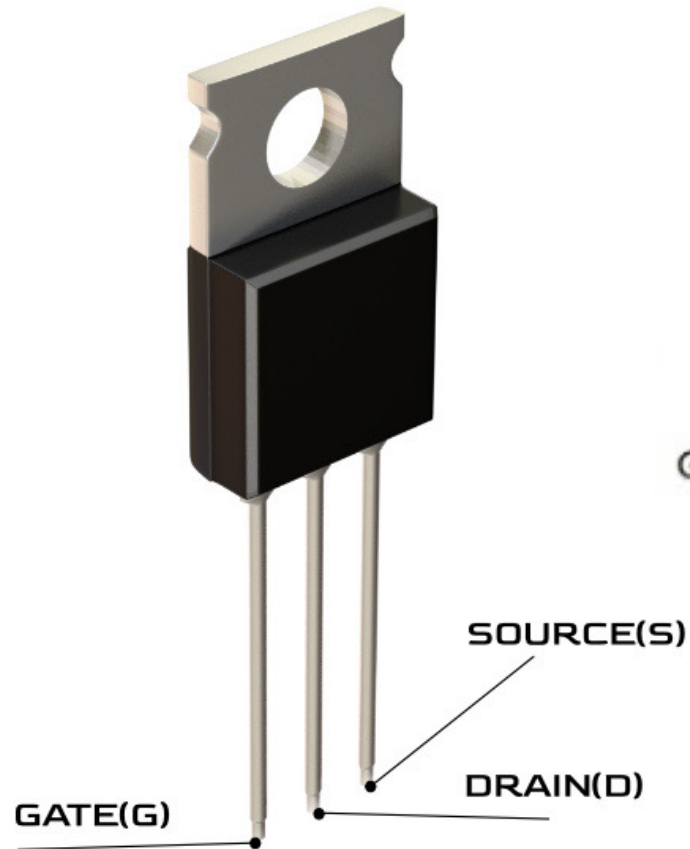


Transistors-101

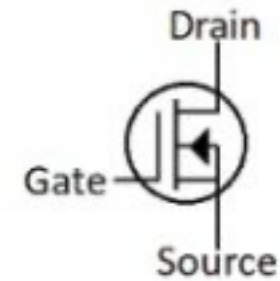
Field-Effect Transistor (FET)
Voltage-controlled amplifiers



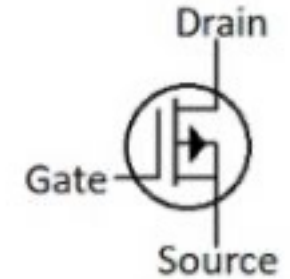
Metal-Oxide-Semiconductor Field-Effect Transistor (MOSFET)



n-channel



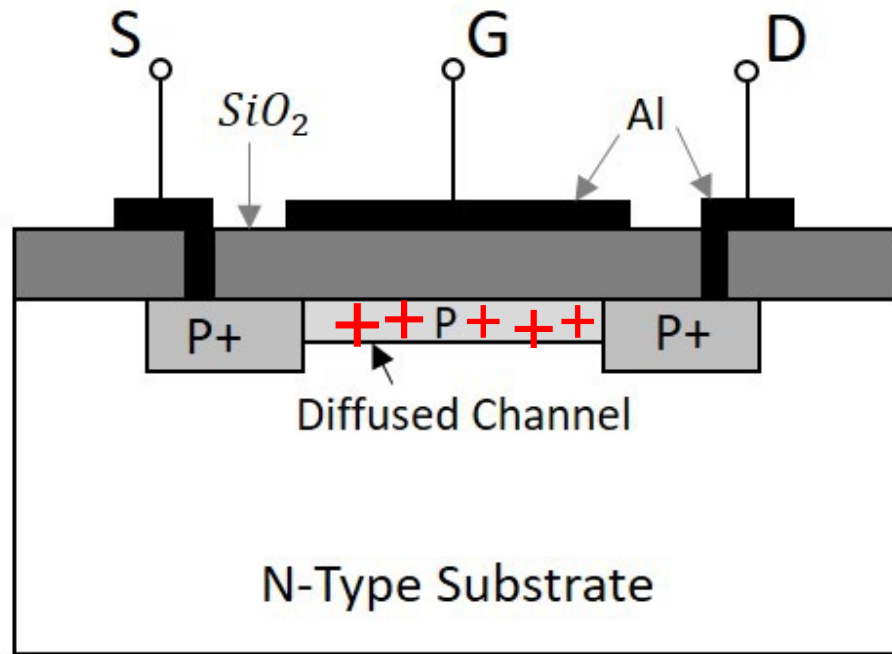
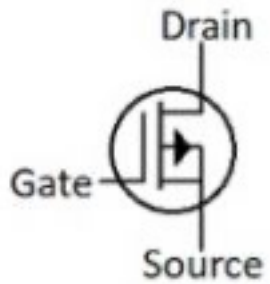
p-channel



Transistors-101

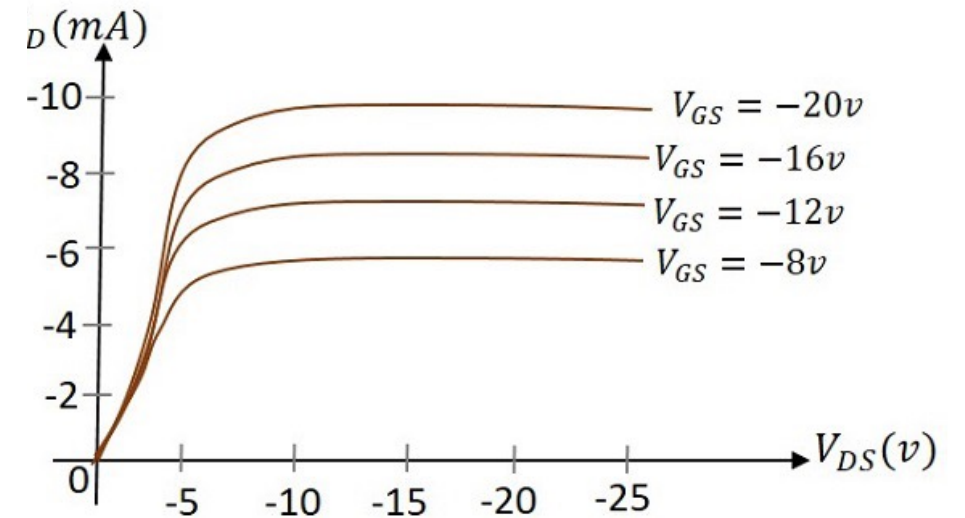
Metal-Oxide-Semiconductor Field-Effect Transistor (MOSFET)

p-channel



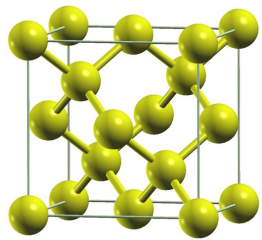
Structure of P-channel MOSFET

Drain Characteristics of MOSFET

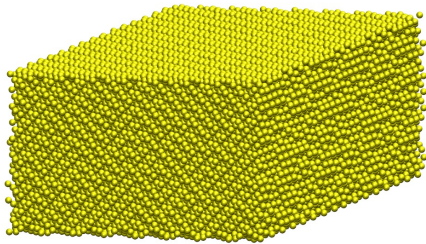


From Atoms to Devices

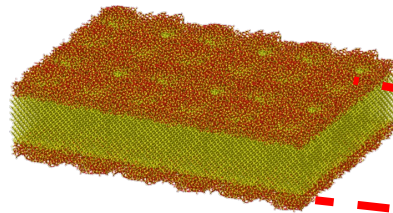
Bulk Silicon



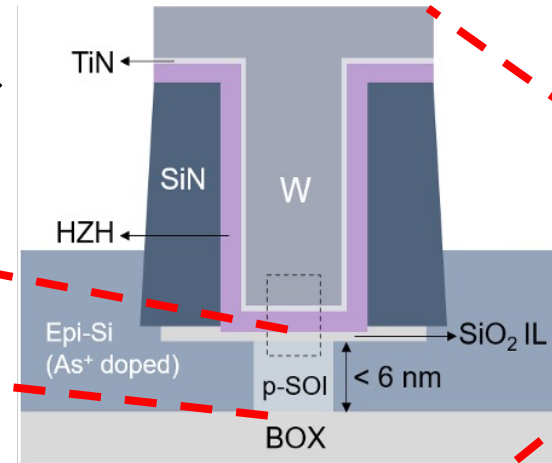
Silicon Channel



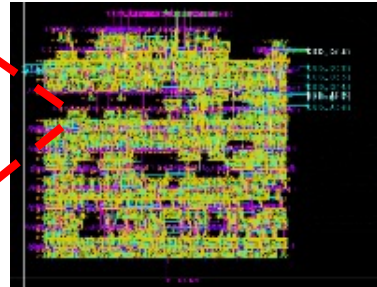
Silicon Channel Heterostructure



Field Effect Transistor



Chip/Chiplet/Circuit

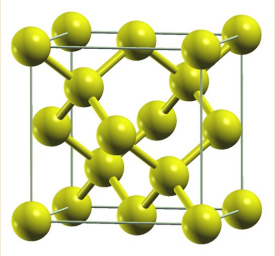


~size of a Coronavirus

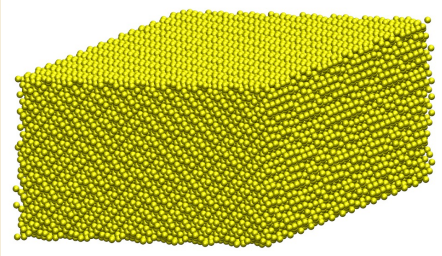
iPhone has 15 billion transistors on the main chip

From Atoms to Devices: Our Efforts

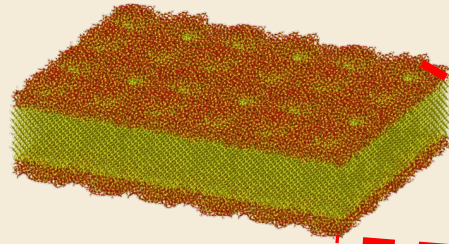
Bulk Silicon



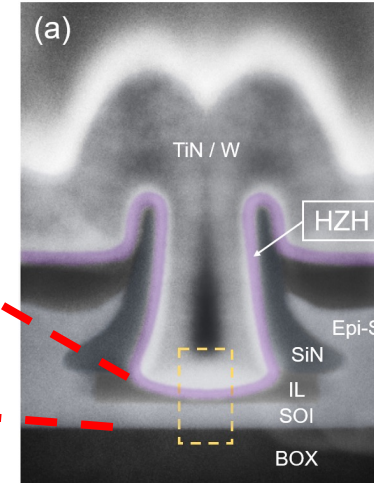
Silicon Channel



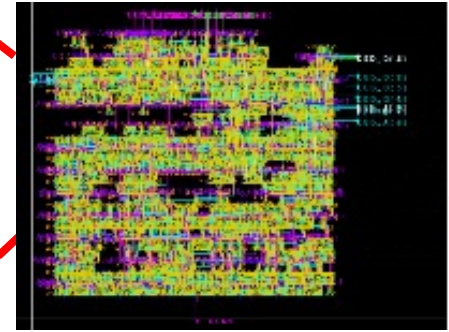
Silicon Channel Heterostructure



Field Effect Transistor



Chip/Chiplet/Circuit



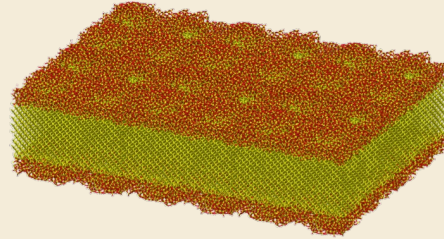
1. Atoms-to-Structures: Thermal and Electronic Properties of Semiconductor Heterostructures

ACS Nano **9** (4), 3820-3828 (2015)
EPJB **88** (3) 73 (2015)

Appl. Phys. Lett. **109**, 053902 (2016)
Phys. Rev. B, **95**(18), 180301 (2017)

Phys. Rev. B, **99**(1), 014207 (2019)
Phys. Rev. Applied **14**, 024004 (2020)

Silicon
Nanostructures



1. Thermal Properties of Semiconductor Heterostructures

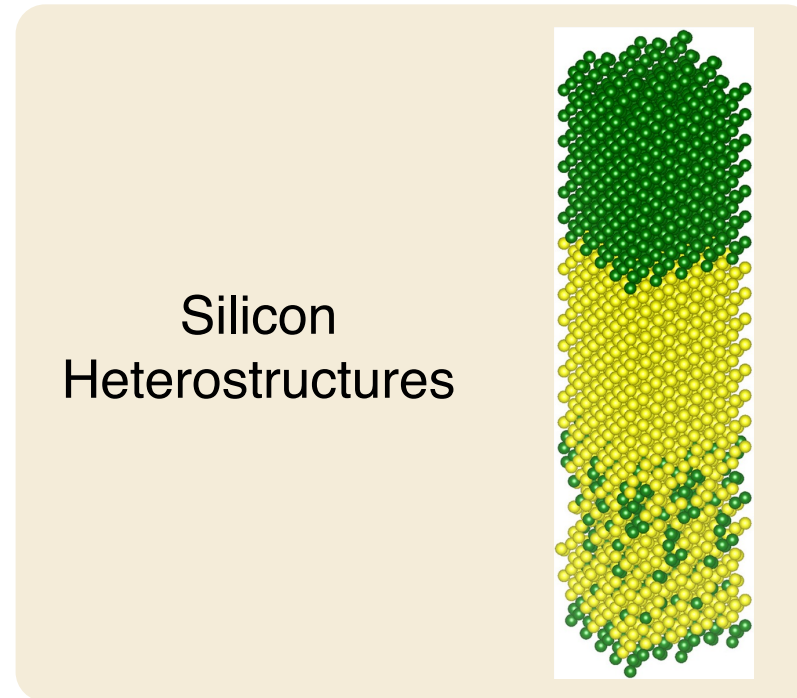


Phys. Rev. B, **99**(1), 014207 (2019)
Appl. Phys. Lett. **115**, 211602 (2019)

J. Electron Mater., **49**, 4431-4442 (2020)
J. Appl. Phys. **129**, 025301 (2021)

J. Mater. Chem. C, **10**, 7525-7542 (2022)
arXiv:2302.00261 (2023)

npj Comput. Mater. **7**, 93 (2021)

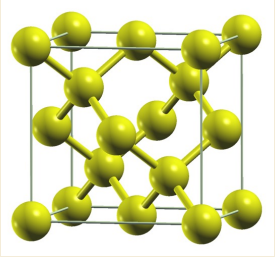


2. Electronic Properties of Semiconductor Heterostructures

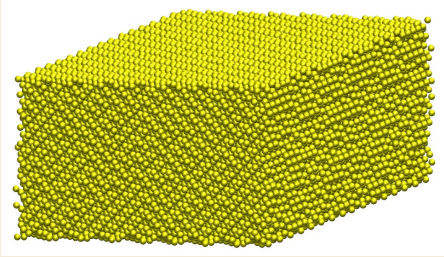


From Atoms to Devices: Our Efforts

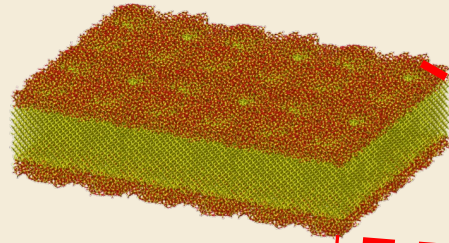
Bulk Silicon



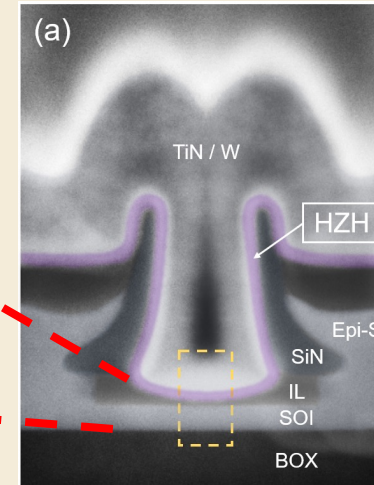
Silicon Channel



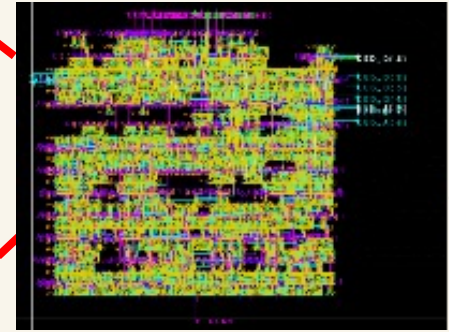
Silicon Channel with Insulating Layer



Field Effect Transistor



Chip/Chiplet/Circuit



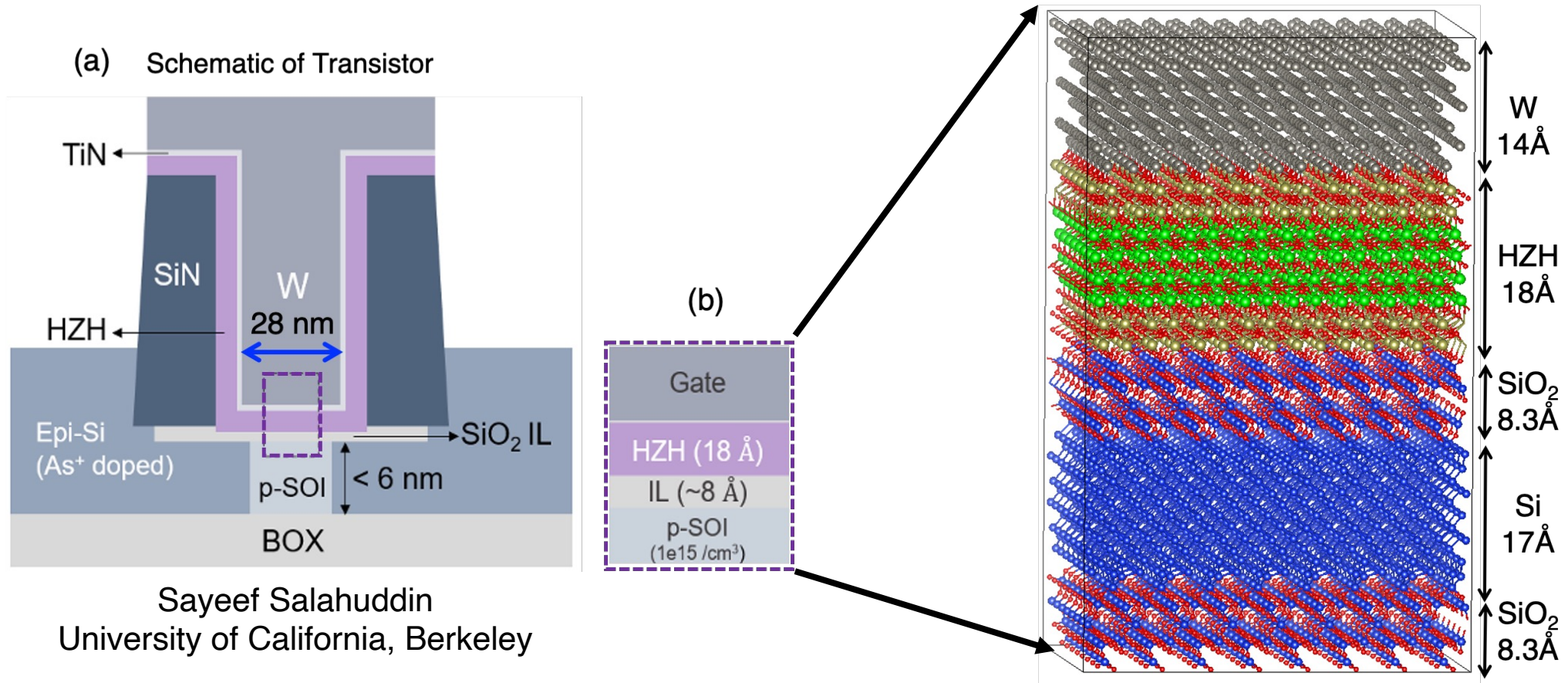
University of California, Berkeley

Purdue University

3. Atoms-to-Circuit: Thermal Model of Microelectronic Systems



Atomistic Model of Transistor

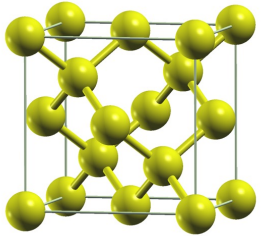


Sayeef Salahuddin
University of California, Berkeley

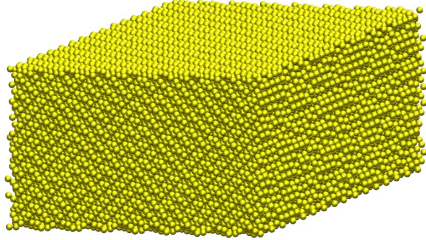
Accelerated learning of interactions using GPUs and machine learning (ML) potentials

From Atoms to Devices: Our Efforts

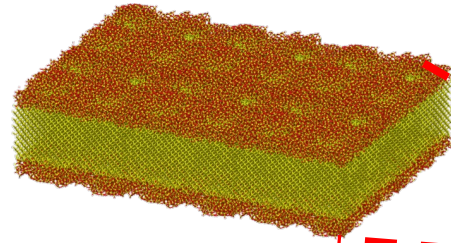
Bulk Silicon



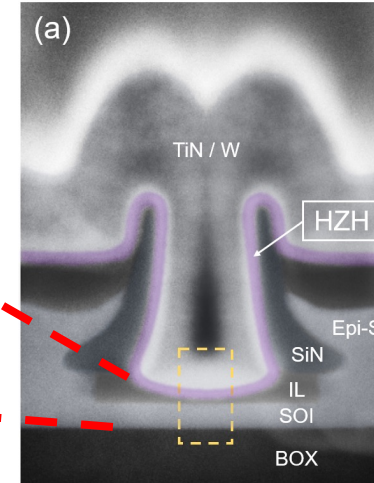
Silicon Channel



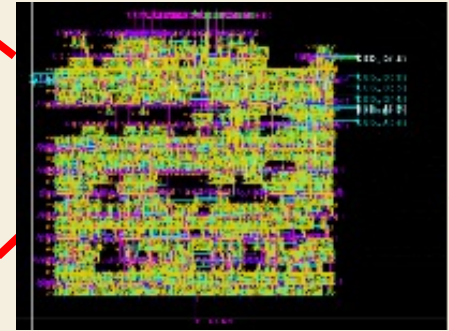
Silicon Channel with Insulating Layer



Field Effect Transistor



Chip/Chiplet/Circuit



4. Reverse model: Predicting thermal properties of structural images

Outline

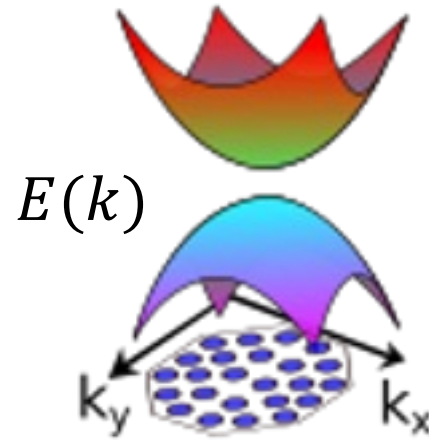
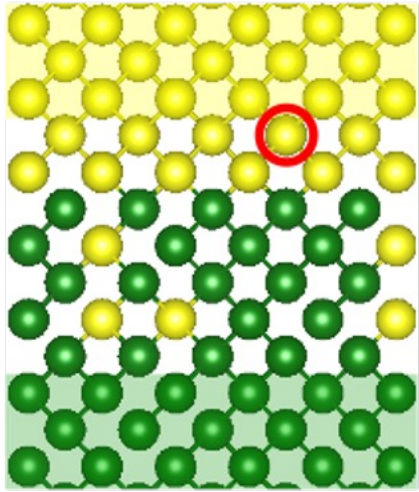
1. Atoms-to-Structures: Electronic Properties of Semiconductor Heterostructures

2. Reverse model: Predicting thermal properties of structural images

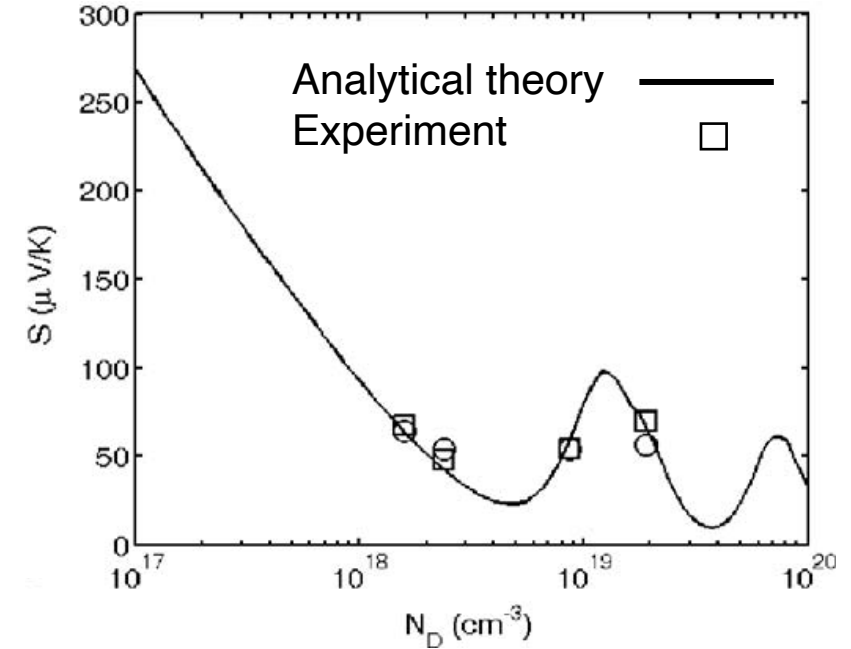
Outline

1. Atoms-to-Structures: Electronic Properties of Semiconductor Heterostructures

Electronic Transport Property Calculation



Brillouin zone sampling



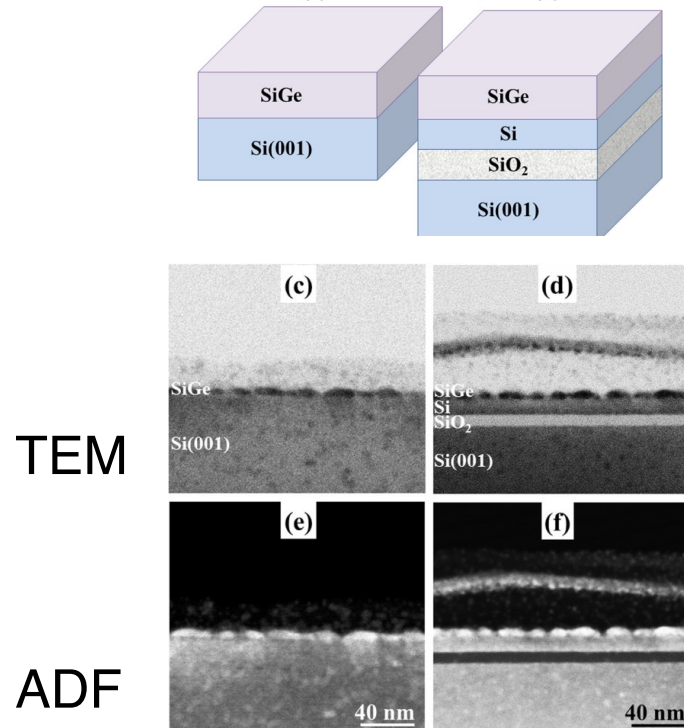
S : Seebeck coefficient or thermopower

$$S = -\frac{\Delta V}{\Delta T}$$

$$\propto \int_{BZ} \frac{d^3k}{4\pi^3} (E(k) - \mu)^a v(k)v(k)\tau(k) \left(-\frac{\partial f_\mu}{\partial E(k)} \right)$$

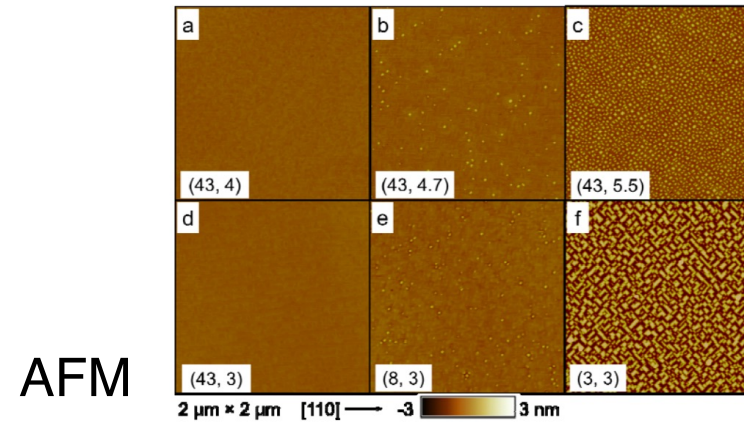
Structural Features of Heterostructures

Presence of islands



Sci Rep **8**, 2891 (2018)

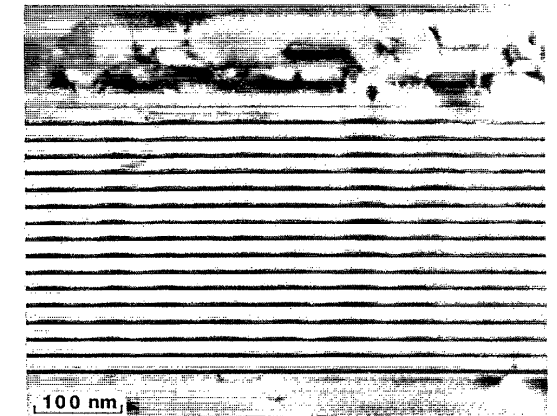
Presence of nanodots



$(\text{Si})_m/(\text{Ge})_n$ SLs
grown on Si(001)

Phys. Rev. Lett. **111**, 115901 (2013)

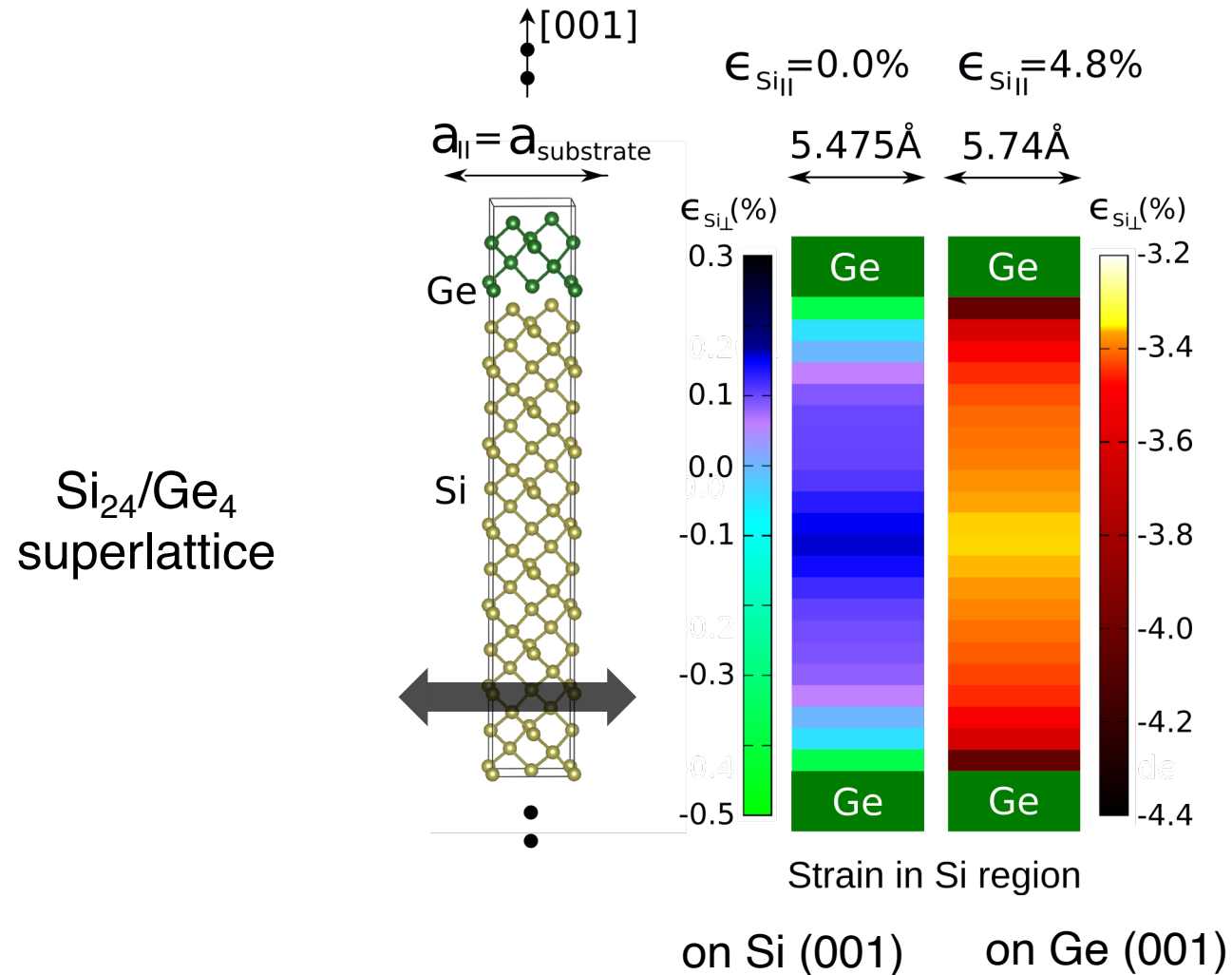
Rough interfaces



$\text{Si}_{0.5}\text{Ge}_{0.5}$ (6nm)/Si (14nm)
grown on Si(001)

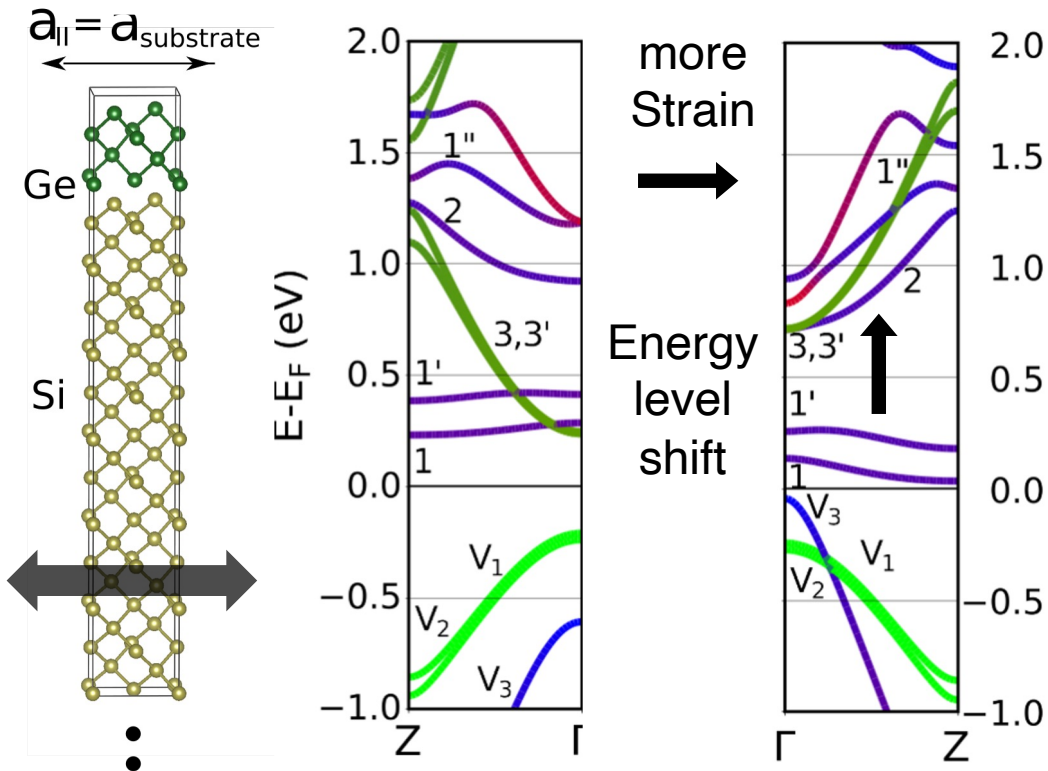
Appl. Phys. Lett., **59** (18), 2242 (1991)

Local Structure of Superlattices

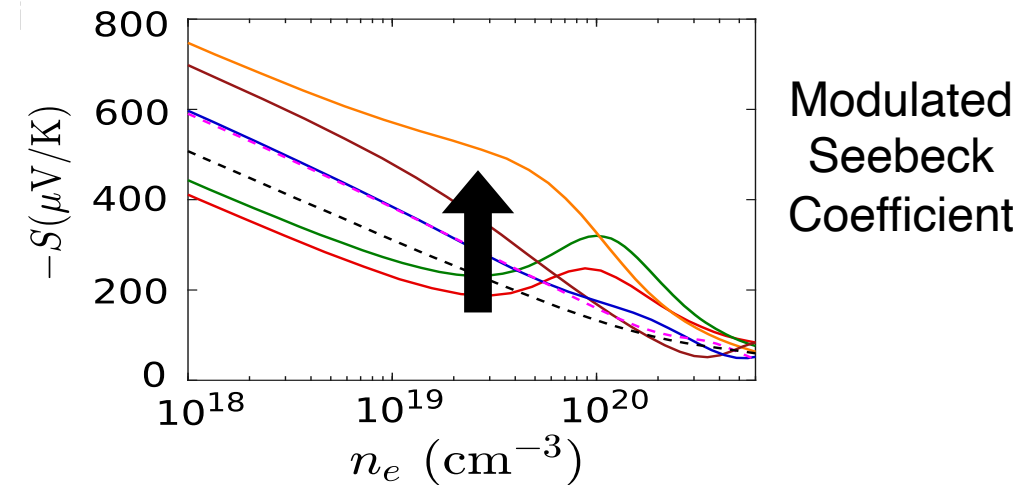


non-uniform
local strain in
heterostructure

Structure-Electronic Property Relationships



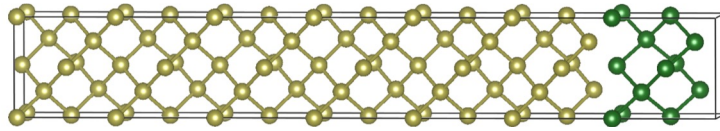
BoltzTrap



Electronic transport of semiconductor heterostructures can be tuned using strain

Approach

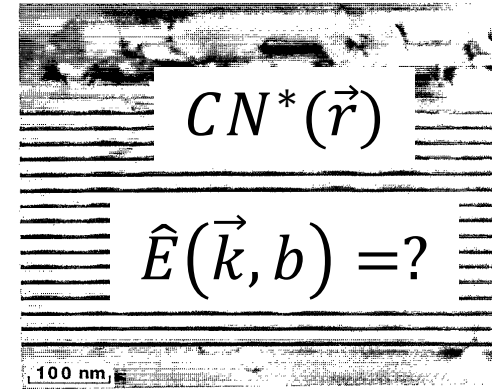
Model systems



Local environment: $CN(\vec{r})$

Energy bands: $E(\vec{k}, b)$

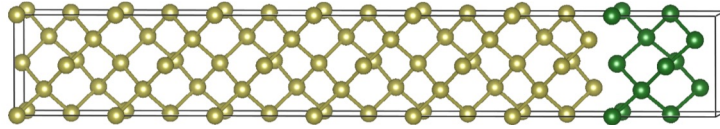
Experimental
heterostructures



Hypothesis: Local structure-energy bands relationships, $f(CN(\vec{r}), E)$, are transferable

Approach

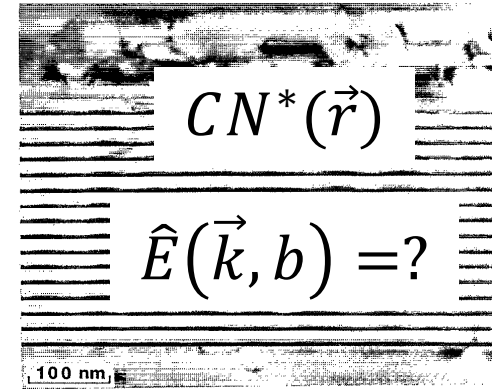
Model systems



Local environment: $CN(\vec{r})$

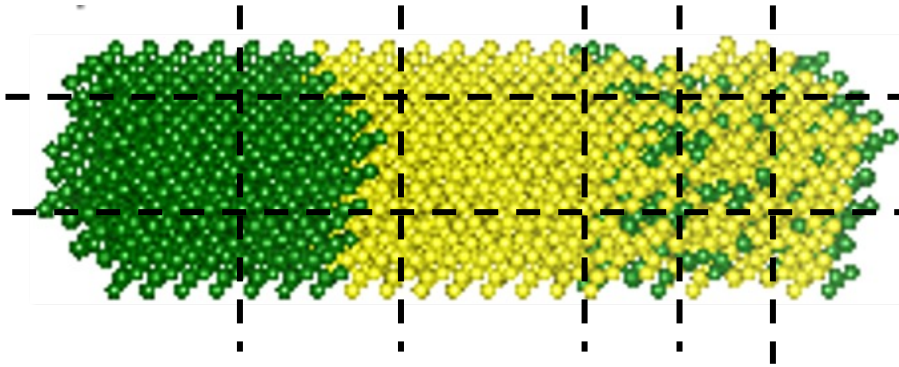
Energy bands: $E(\vec{k}, b)$

Experimental
heterostructures



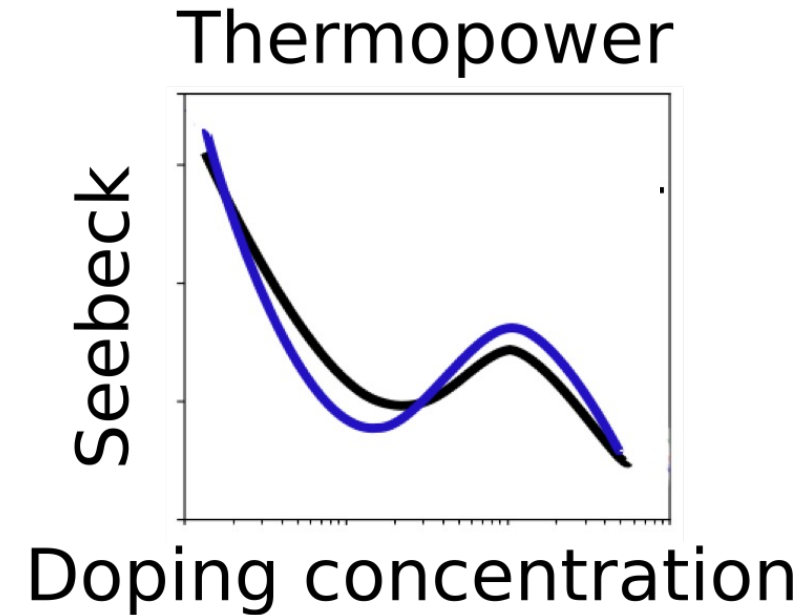
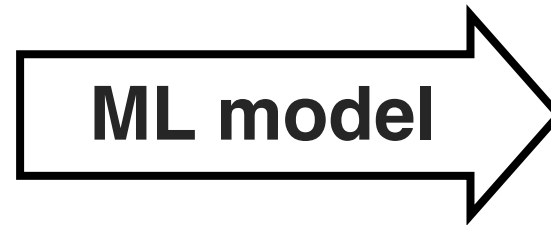
1. Train ML models to predict $f(CN(\vec{r}), E)$, for unknown local environments
2. Sum local properties to get global properties

Forward Electronic Transport ML Model



~600 atoms

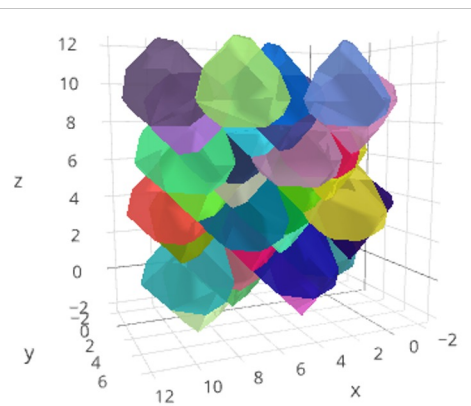
16-atom Si/Ge ordered and disordered units



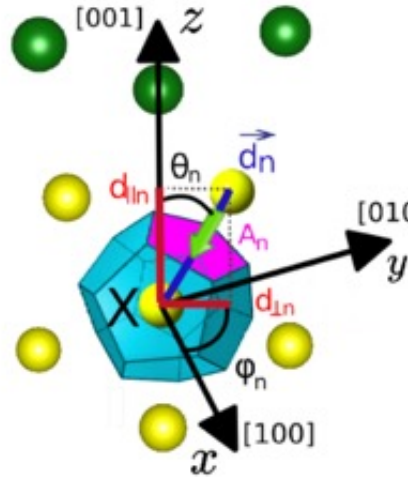
ML model extrapolates structure-electronic property relationships to larger systems, bypassing expensive computation

Descriptors of $CN(\vec{r})$

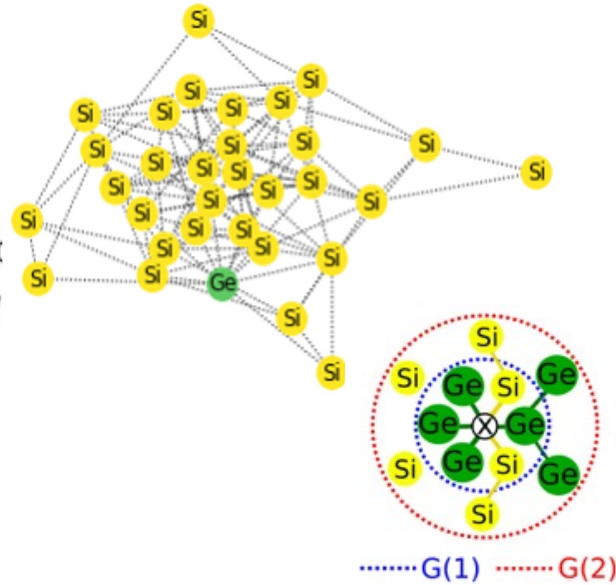
Voronoi tessellation (VT)



Voronoi cell



Crystal graph



1. Perform VT of crystal structure
2. Calculate statistics of VT derived attributes
3. Construct CG through adjacent cells
4. Calculate order parameters

Phys. Rev. **77**, 669 (1950)

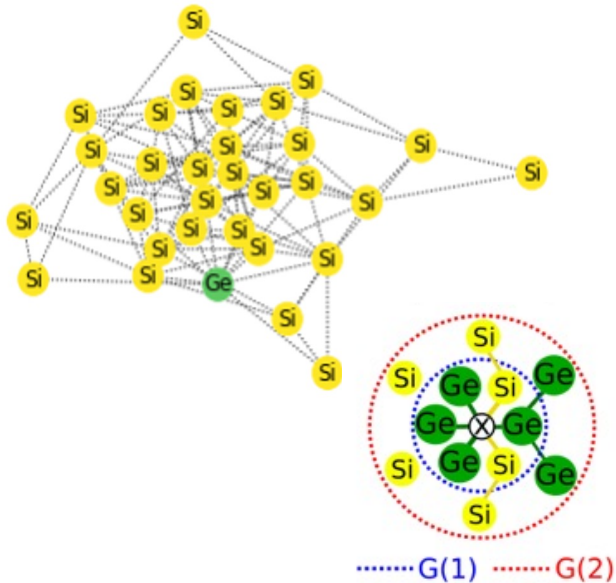
Phys. Rev. B **96**, 024104 (2017)

npj Comput Mater **7**, 93 (2021)

<https://github.com/CUANTAM/Crystal-Graph-Features>

Adequate Representations: Directionality

Crystal graph



Order parameters

$$Q_X^{\Omega, \text{order}} = \sum_{\text{paths in CG}} \prod_{\text{steps}}^{\text{order}} \frac{\overline{\omega}_n A_n \delta_{n,X}}{\underbrace{\sum_{\text{cell}} \overline{\omega}_a A_a}_{\text{all steps}} - \underbrace{\sum_{\text{cell}} \overline{\omega}_b A_b}_{\text{backtracking steps}}}$$

species aware

Directional bias:

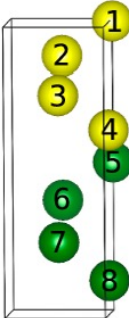
$$\overline{\omega}_n = (|\cos \phi_n \sin \theta_n|, |\sin \phi_n \sin \theta_n|, |\cos \theta_n|)$$

- Unique representation of $CN(\vec{r})$
- Quantify proximity to an interface
- Representative of directionality or inhomogeneity
- Scalable to large system sizes
- Obtainable from imaging data

npj Comput Mater 7, 93 (2021)

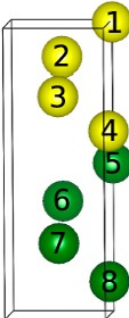
<https://github.com/CUANTAM/Crystal-Graph-Features>

Descriptors of $CN(\vec{r})$: Input to ML

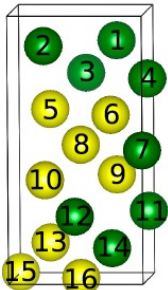


Atom #	$Q_{x,1}$	$Q_{y,1}$	$Q_{z,1}$	$Q_{x,2}$	$Q_{y,2}$	$Q_{z,2}$	$Q_{x,3}$	$Q_{y,3}$	$Q_{z,3}$
Si 1	0.55	0.55	0.51	0.49	0.49	0.45	0.36	0.36	0.29
Si 2	0.95	0.95	0.89	0.64	0.64	0.53	0.43	0.43	0.34
Si 3	0.95	0.95	0.89	0.64	0.64	0.53	0.43	0.43	0.34
Si 4	0.55	0.55	0.51	0.49	0.49	0.45	0.36	0.36	0.29
Ge 5	0.53	0.53	0.49	0.47	0.47	0.46	0.37	0.37	0.30
Ge 6	0.97	0.97	0.94	0.70	0.70	0.58	0.47	0.47	0.36
Ge 7	0.97	0.97	0.94	0.70	0.70	0.58	0.47	0.47	0.36
Ge 8	0.53	0.53	0.49	0.47	0.47	0.46	0.37	0.37	0.30

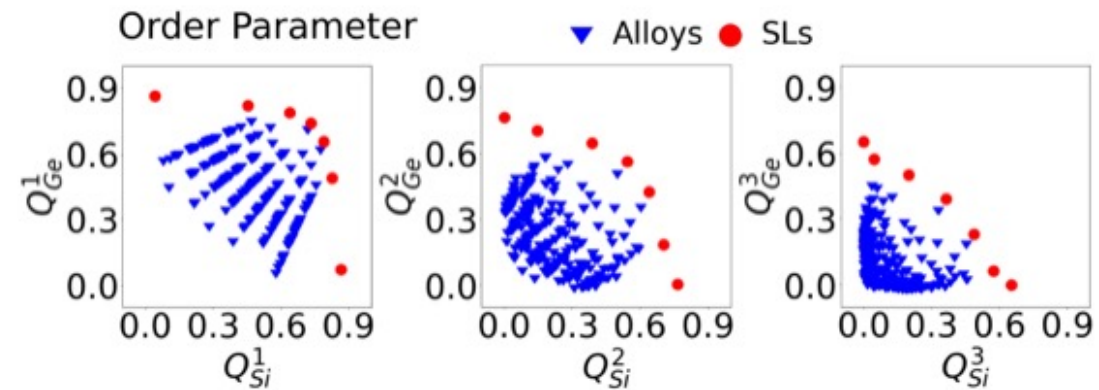
Descriptors of $CN(\vec{r})$: Input to ML



Atom #	$Q^{x,1}$	$Q^{y,1}$	$Q^{z,1}$	$Q^{x,2}$	$Q^{y,2}$	$Q^{z,2}$	$Q^{x,3}$	$Q^{y,3}$	$Q^{z,3}$
Si 1	0.55	0.55	0.51	0.49	0.49	0.45	0.36	0.36	0.29
Si 2	0.95	0.95	0.89	0.64	0.64	0.53	0.43	0.43	0.34
Si 3	0.95	0.95	0.89	0.64	0.64	0.53	0.43	0.43	0.34
Si 4	0.55	0.55	0.51	0.49	0.49	0.45	0.36	0.36	0.29
Ge 5	0.53	0.53	0.49	0.47	0.47	0.46	0.37	0.37	0.30
Ge 6	0.97	0.97	0.94	0.70	0.70	0.58	0.47	0.47	0.36
Ge 7	0.97	0.97	0.94	0.70	0.70	0.58	0.47	0.47	0.36
Ge 8	0.53	0.53	0.49	0.47	0.47	0.46	0.37	0.37	0.30



Atom #	$Q^{x,1}$	$Q^{y,1}$	$Q^{z,1}$	$Q^{x,2}$	$Q^{y,2}$	$Q^{z,2}$	$Q^{x,3}$	$Q^{y,3}$	$Q^{z,3}$
Ge 1	0.50	0.55	0.48	0.21	0.21	0.15	0.09	0.08	0.05
Ge 2	0.55	0.50	0.48	0.23	0.21	0.17	0.08	0.08	0.04
Ge 3	0.55	0.50	0.48	0.21	0.21	0.15	0.08	0.09	0.05
Ge 4	0.50	0.55	0.48	0.21	0.23	0.17	0.08	0.08	0.04
Si 5	0.34	0.34	0.30	0.22	0.22	0.20	0.05	0.05	0.04
Si 6	0.34	0.34	0.30	0.21	0.21	0.20	0.05	0.05	0.04
Ge 7	0.10	0.10	0.19	0.05	0.05	0.08	0.02	0.02	0.03
Si 8	0.83	0.83	0.83	0.11	0.11	0.09	0.03	0.03	0.03
Si 9	0.34	0.37	0.34	0.22	0.23	0.22	0.05	0.05	0.03
Si 10	0.37	0.34	0.34	0.23	0.22	0.22	0.05	0.05	0.03
Ge 11	0.34	0.29	0.26	0.09	0.10	0.08	0.02	0.02	0.02
Ge 12	0.29	0.34	0.26	0.10	0.09	0.08	0.02	0.02	0.02
Si 13	0.45	0.45	0.49	0.05	0.05	0.03	0.02	0.02	0.02
Ge 14	0.46	0.46	0.51	0.08	0.08	0.08	0.03	0.03	0.02
Si 15	0.30	0.30	0.21	0.09	0.09	0.07	0.01	0.01	0.01
Si 16	0.30	0.30	0.21	0.09	0.09	0.07	0.01	0.01	0.01



Training ML Model

1. Global features
 2. Statistical parameters of VT derived attributes
 3. Statistical parameters of order parameters
- } $CN(\vec{r})$
4. Electronic band structures: $E(\vec{k}, b)$

Train ML models to learn $f(CN(\vec{r}), E(\vec{k}, b))$
and predict $\hat{E}(\vec{k}, b)$, given $CN^*(\vec{r})$

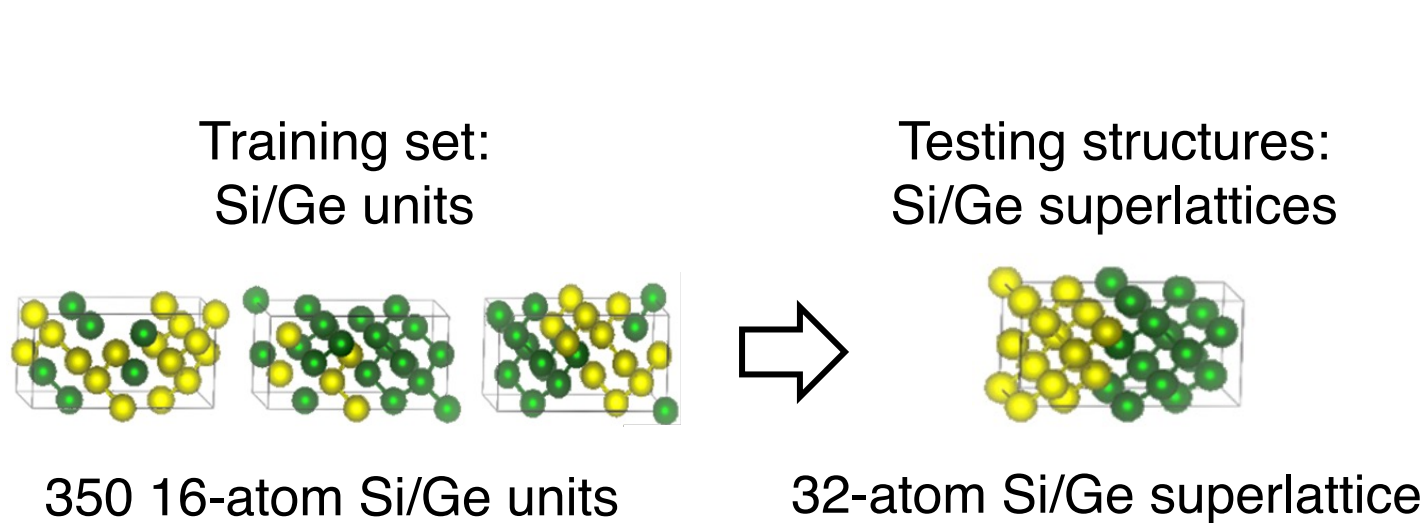


PBE exchange-correlation functional

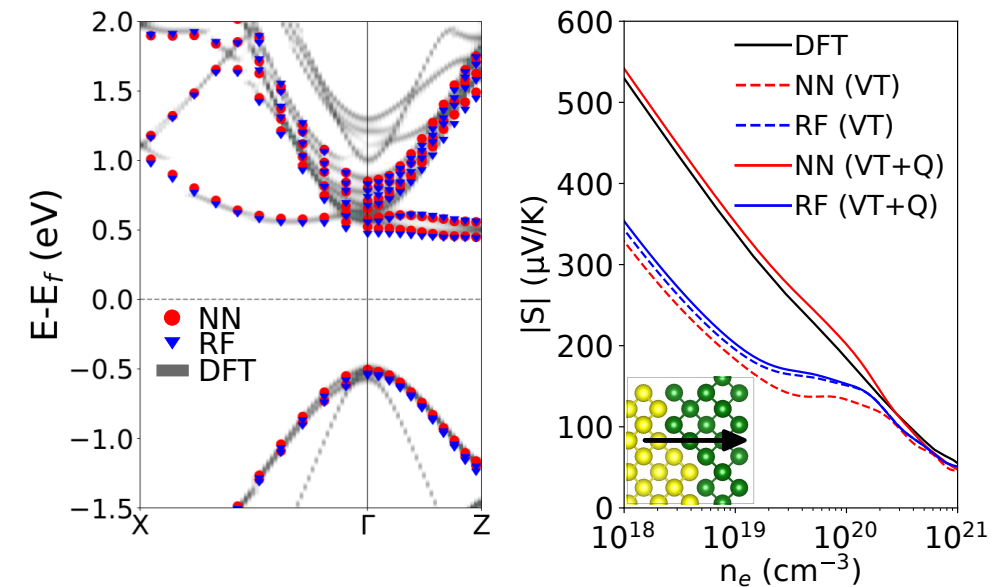
Generalized gradient approximation

BoltzTrap

Testing Validity of Hypothesis: Transferable $f(CN(\vec{r}), E(\vec{k}, b))$ Relationships



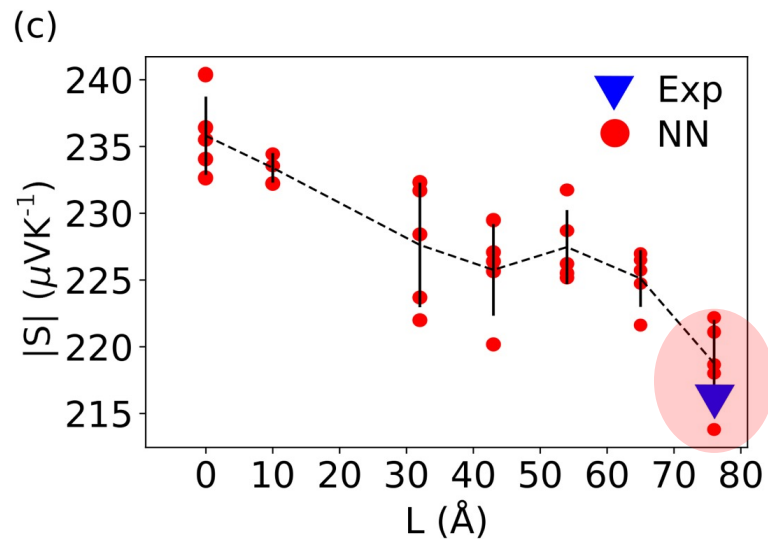
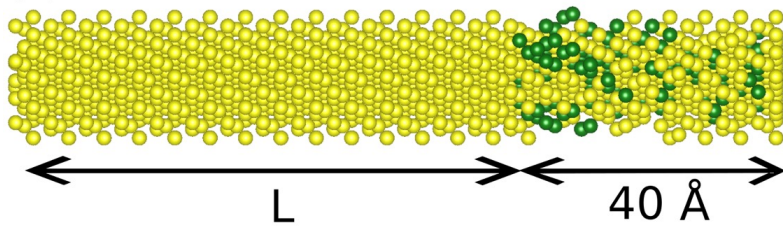
Superlattice with imperfect layers



Able to predict electronic properties of larger structures after being trained on 16-atom units

Forward Electronic Transport ML Model

Bulk-alloy interface



ML-predicted $E(\mathbf{k}, \mathbf{b})$ used to predict electronic properties of ~ 600 atom semiconductor heterostructure

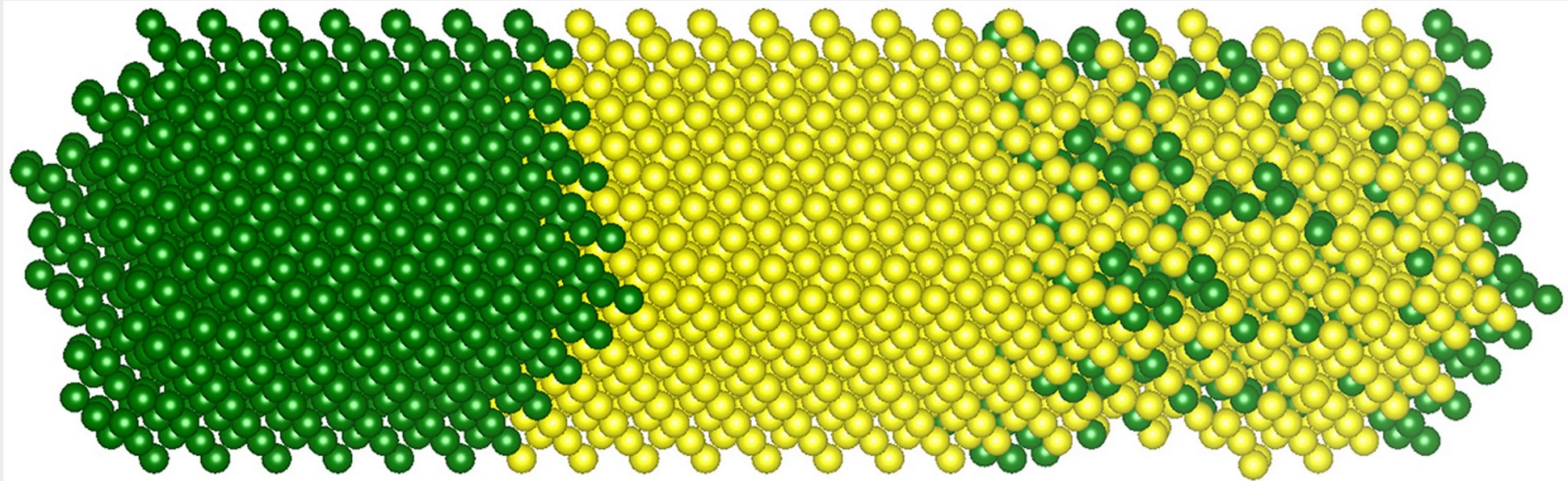
npj Comput. Mater. **7**, 93 (2021)

NEWS

ARTIFICIAL INTELLIGENCE

Physicists Teach AI to Simulate Atomic Clusters >

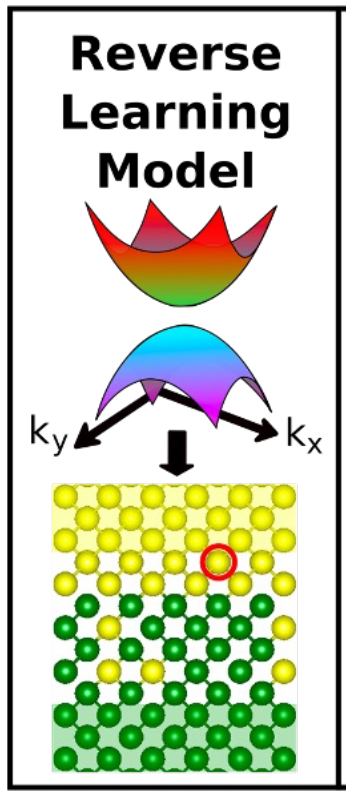
Physics-informed machine learning might help verify microchips

BY MATTHEW HUTSON | 02 JUL 2021 | 3 MIN READ | 

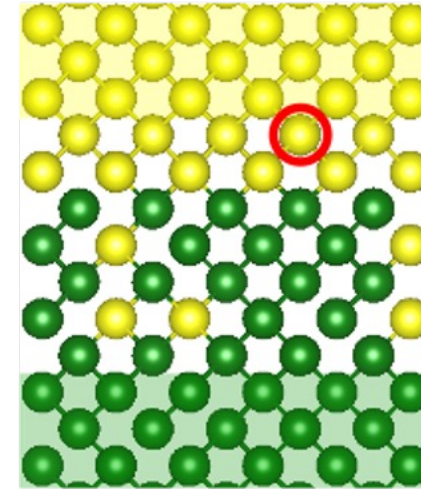
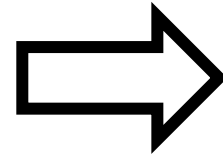
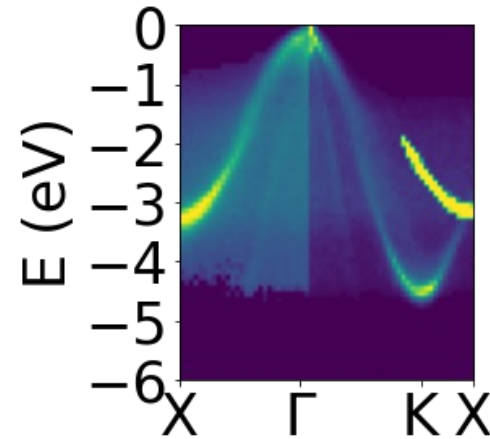
Representative configuration of a fabricated heterostructure. Target S of fabricated heterostructures are computed from $E(k,b)$ using BTE. UNIVERSITY OF COLORADO BOULDER/NPJ COMPUTATIONAL MATERIALS

Reverse Model

Extract atomic structures from spectroscopy images



Angle-resolved photo electron spectra
(ARPES)



Pimachev and Neogi, arXiv:2302.00261 (2023)

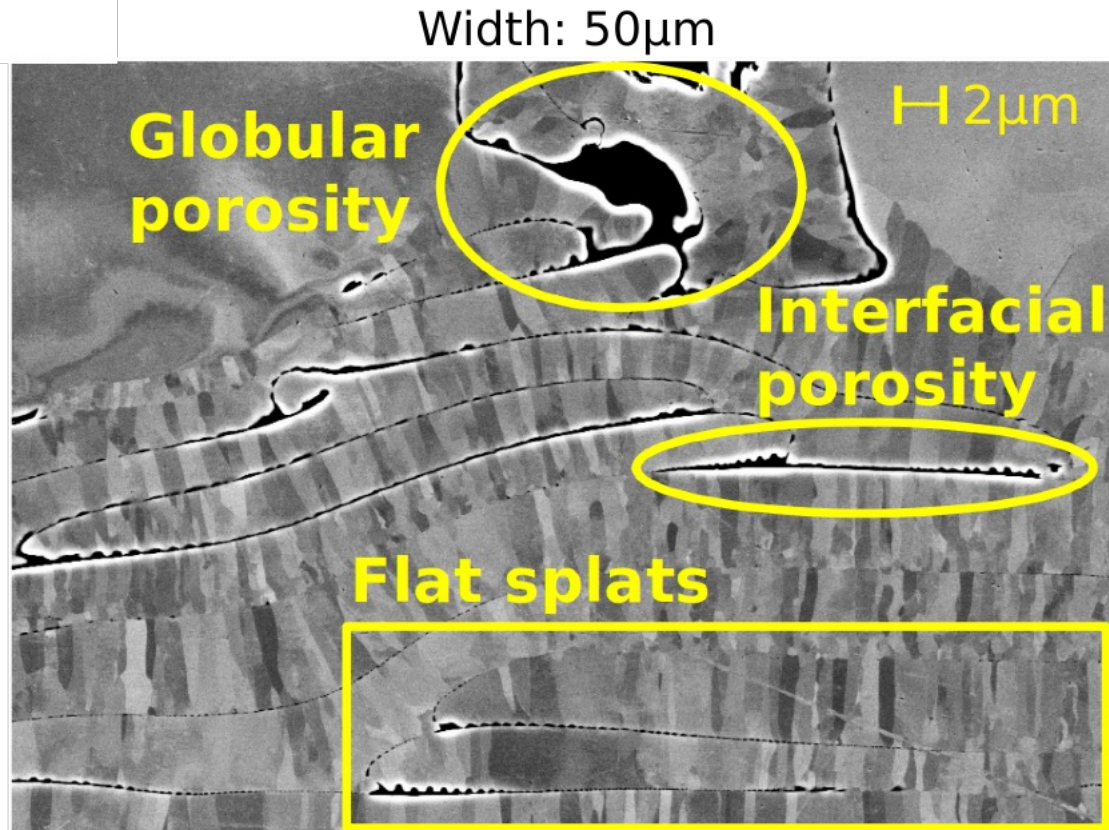
Outline

1. Atoms-to-Structures: Electronic Properties of Semiconductor Heterostructures

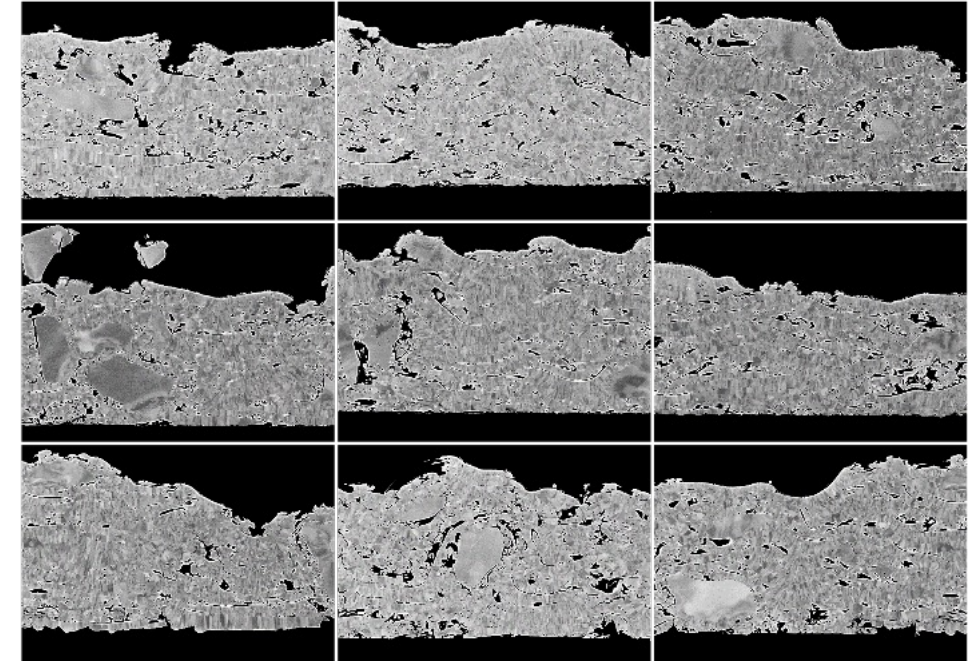
2. Reverse model: Predicting thermal properties of structural images

Thermal Sprayed Coatings

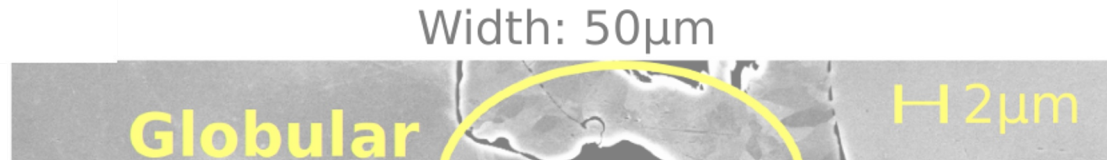
Two-Dimensional (2D) Backscatter Electron Images of Niobium Thermal Spray Coatings



(i) Width: 160 μ m 587px, Height: 112 μ m 410px



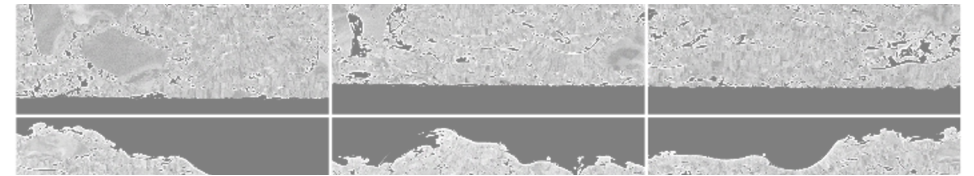
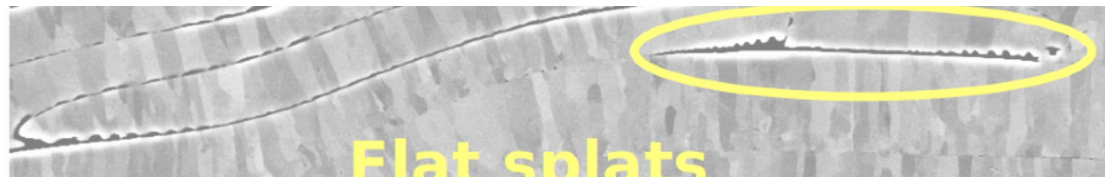
Thermal Sprayed Coatings



(i) Width: 160 μ m 587px, Height: 112 μ m 410px



Microscopic structural features that affect thermal properties, eventually durability and lifetime of coatings

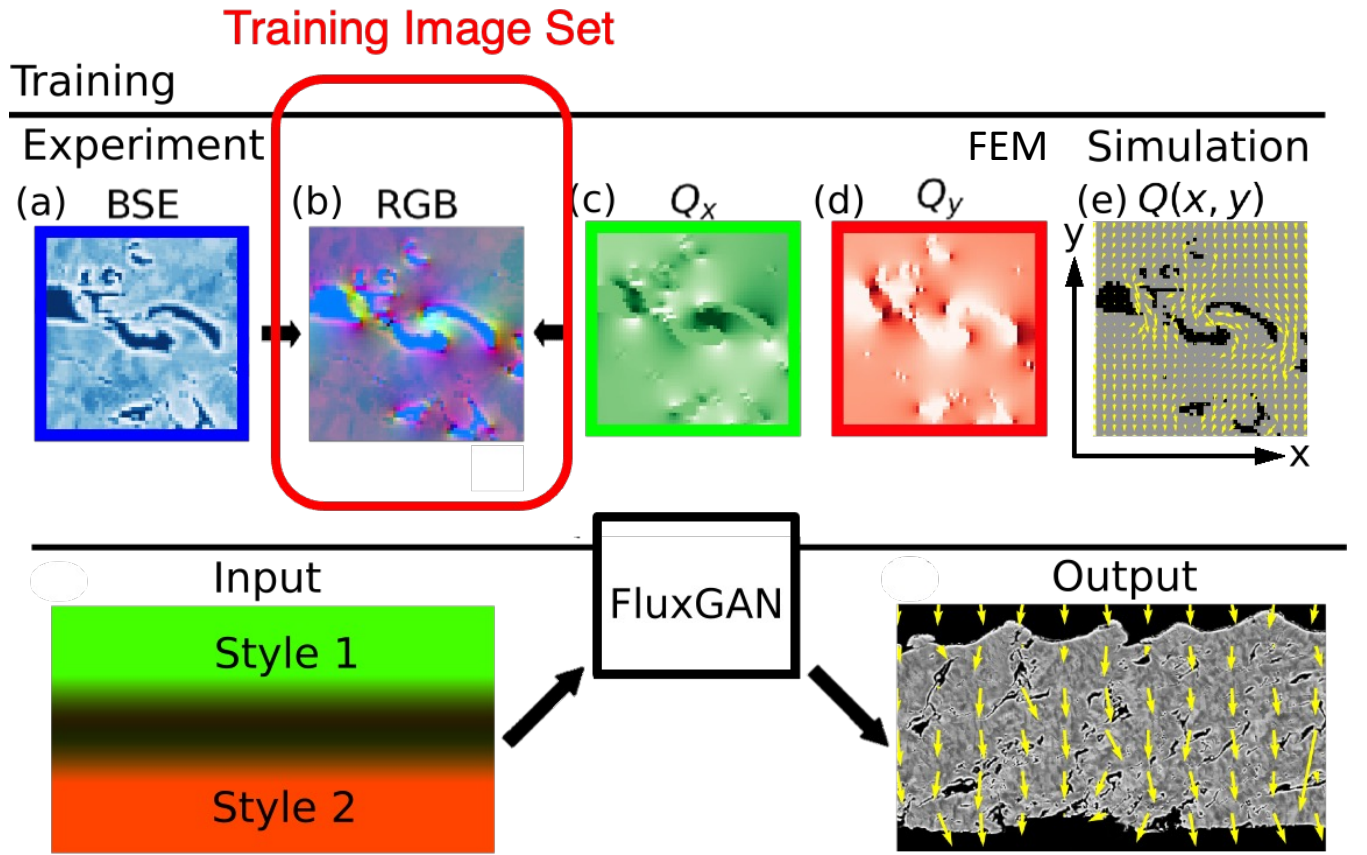


How do different 'classes' of nano-to-microscale features affect thermal properties?

FluxGAN Model

Generates New Coating Images for Input Style Maps

Model Workflow



Training Set

RGB images with channels

Blue: Experimental backscatter electron (BSE) images;

Red: FEM computed top-to-bottom heat flux;

Green: FEM computed left-to-right heat flux;

Augmented with new images obtained by slicing BSE images into smaller images and small rotations

Learning

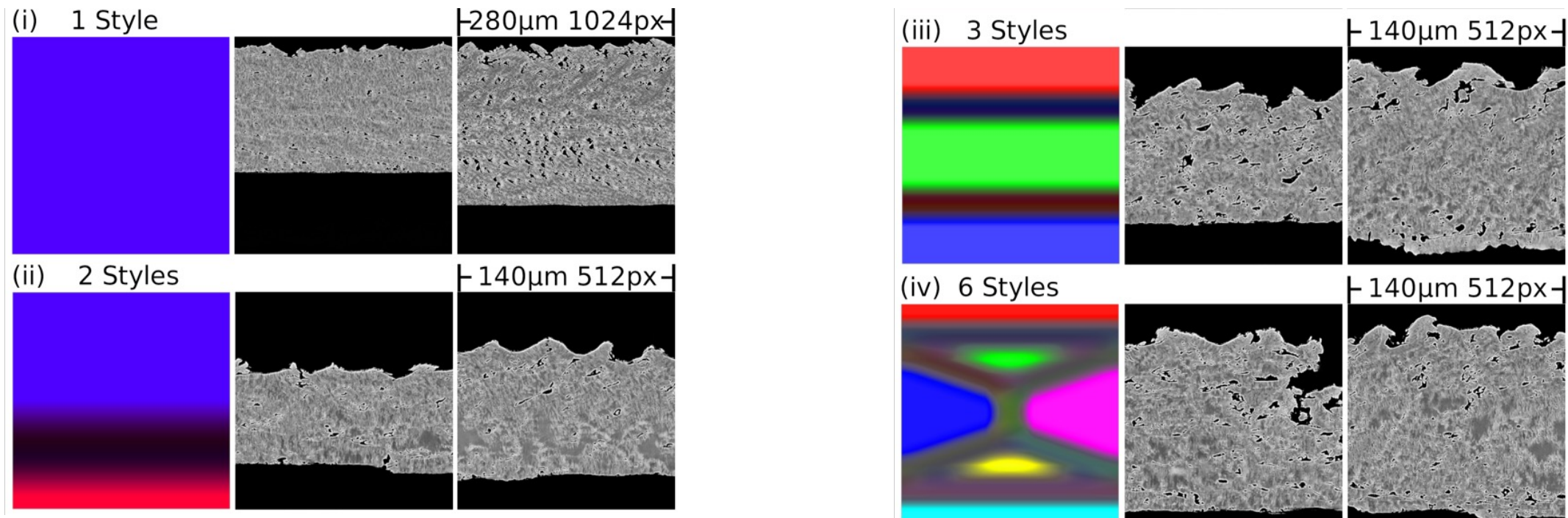
Unsupervised learning of features (styles) in RGB images

Output

Model generates structural images for styles provided as input

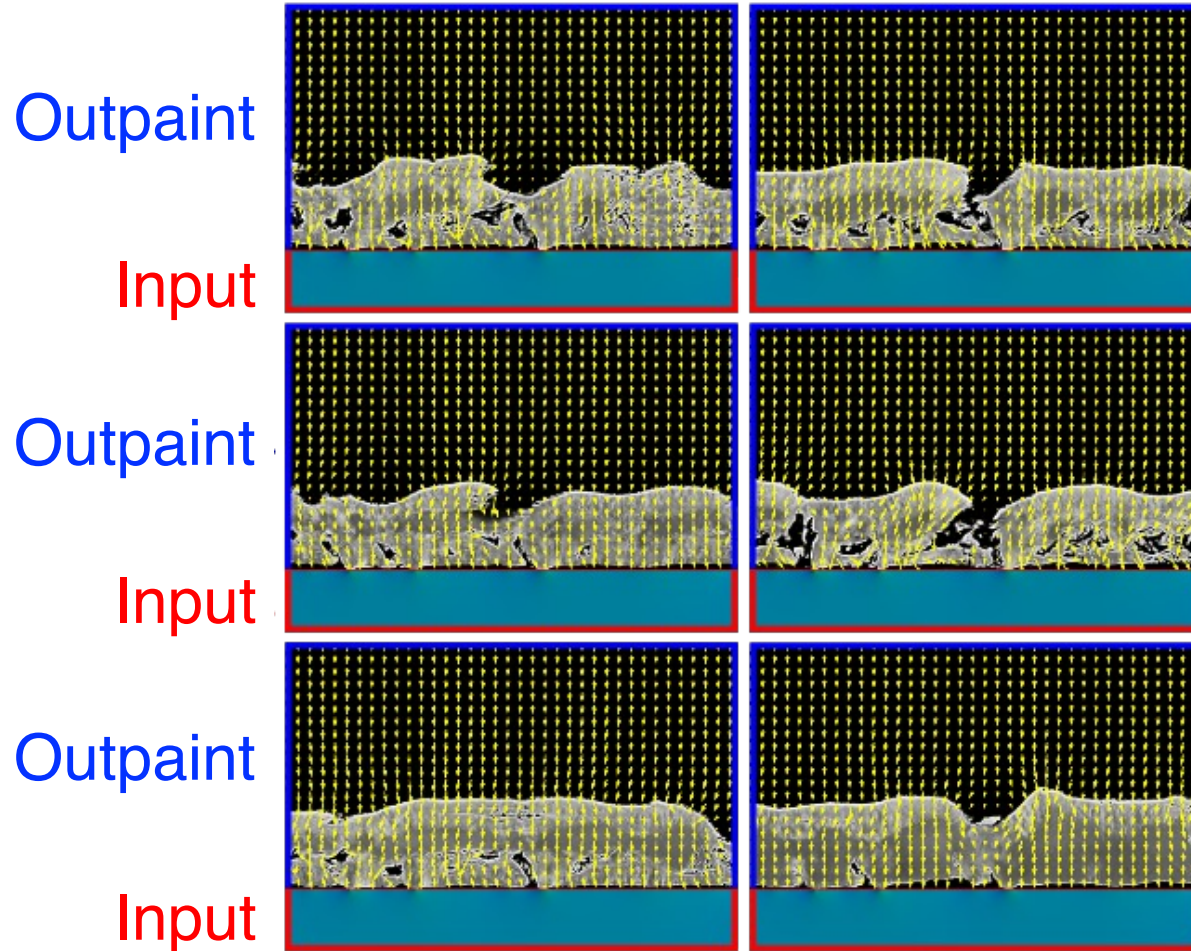
Unsupervised Learning of 'Styles'

Styles { define different 'classes' of nano-to-microscale features of coatings
are closely associated with distribution of heat flux in coatings

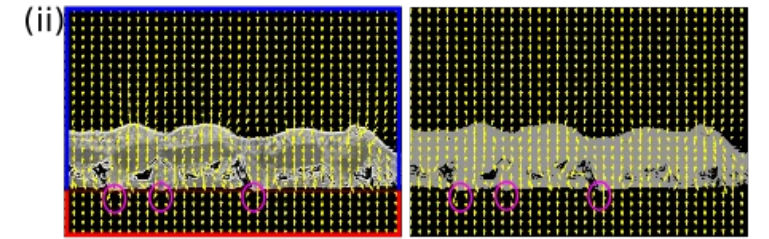


Styles can be associated with processing parameters

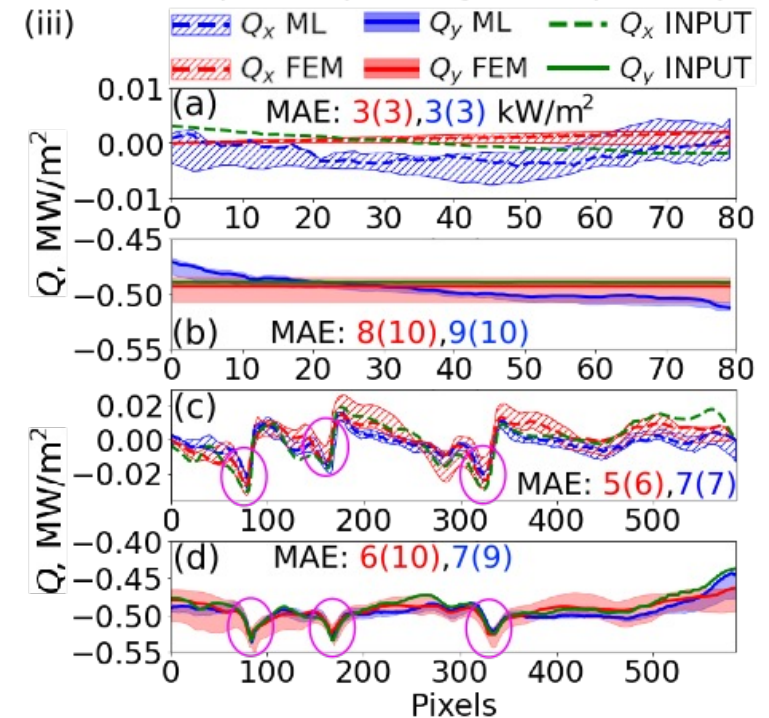
Guided Image Generation for Target Heat Flux



Validation against FEM results

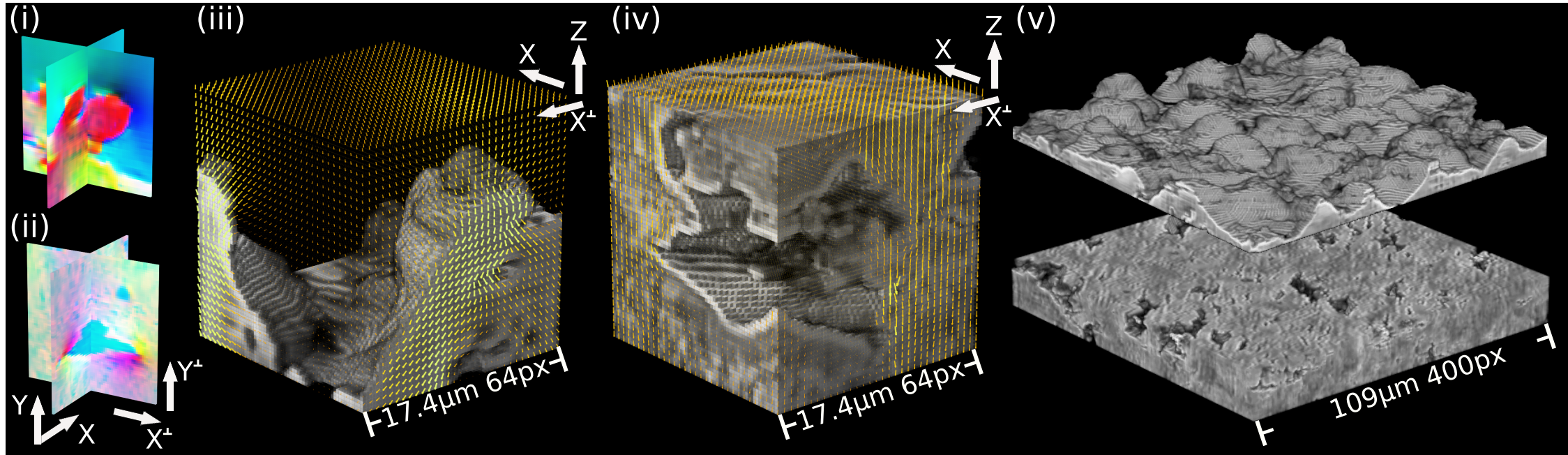


Width: 160 μ m 587px, Height: 109 μ m 400px



From 2D to 3D

Pimachev, Settipalli and Neogi. arXiv preprint arXiv:2310.04622 (2023)



Provide information about inner structures difficult to access from outside

FluxGAN Model

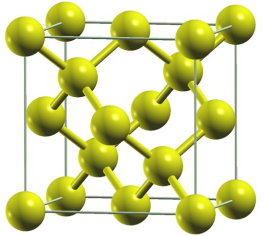
GAN: Generative Adversarial Network

1. is developed using **9** experimental images
2. generates new structures **AND** physical phenomena of interest
3. provides guides for synthesis (e.g., styles created due to spray rate)
4. provides insights to predict materials reliability
5. can be easily generalized to other 2D structures/materials
6. as well as 3D structures

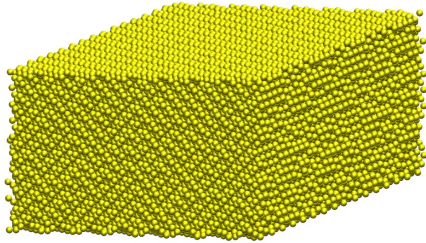
Pimachev, Settupalli and Neogi. arXiv preprint arXiv:2310.04622 (2023)

From Atoms to Devices: Summary

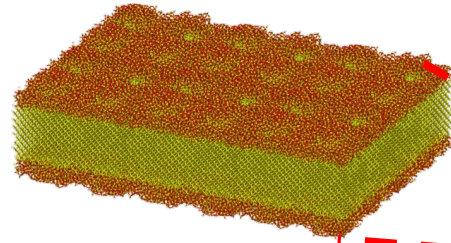
Bulk Silicon



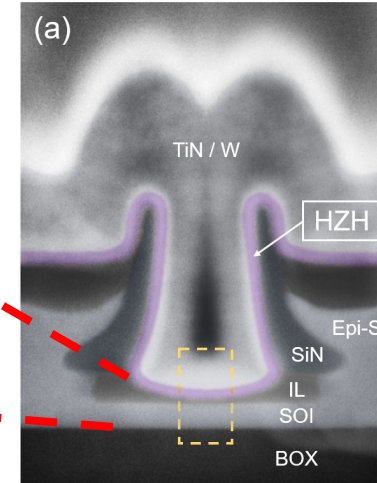
Silicon Channel



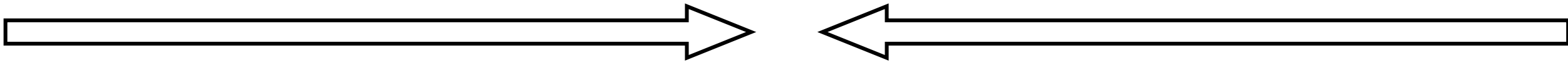
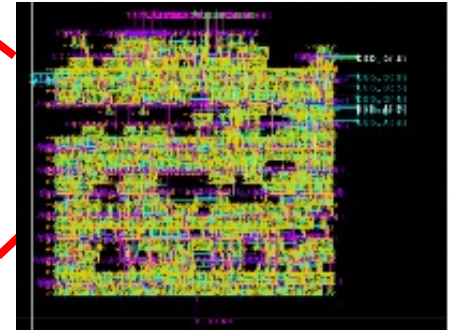
Silicon Channel with Insulating Layer



Field Effect Transistor



Chip/Chiplet/Circuit



Takeaway messages

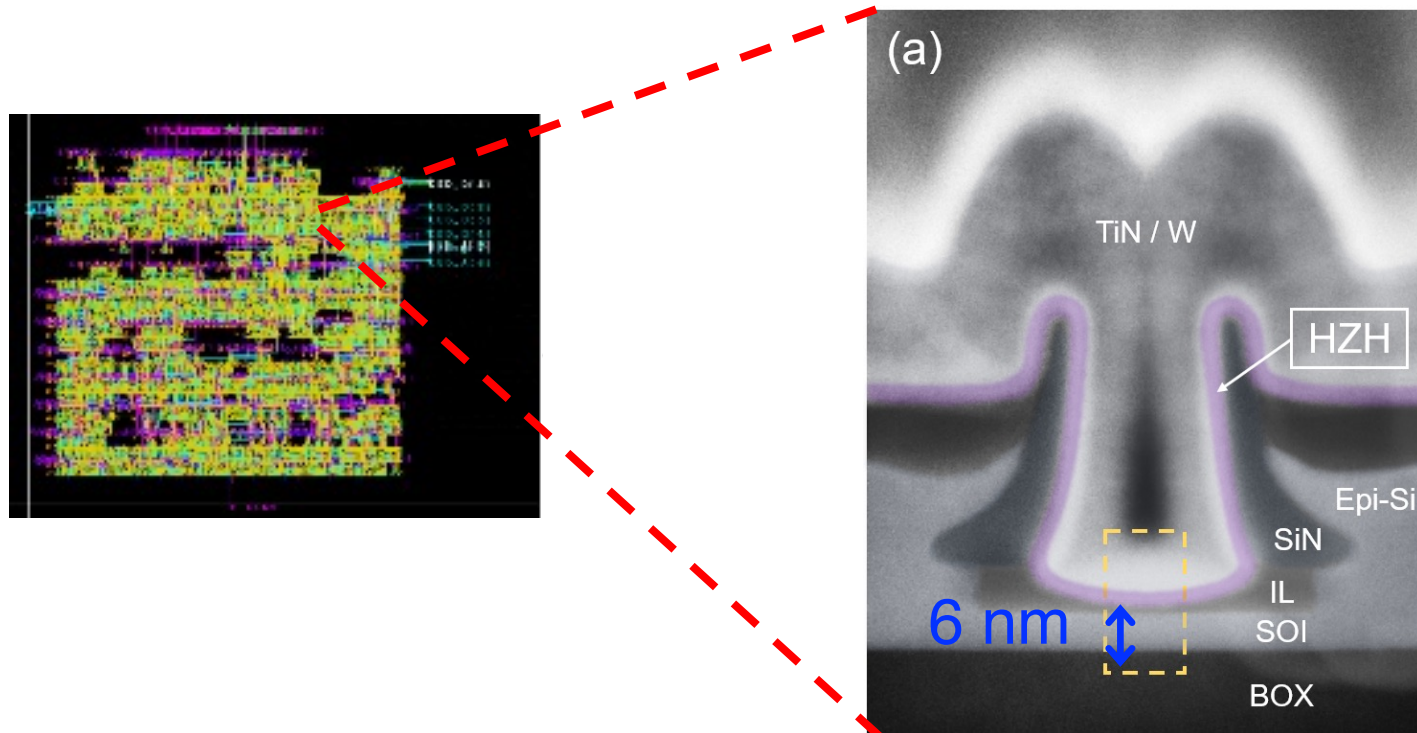
Physics input combined with machine learning approaches can greatly

- Facilitate theory-experiment relationship
- Predict materials behavior in complex devices
- Allow application of basic physics knowledge for device design

Thank you!

Back up slides

Atom-to-Circuit Thermal Model of Microelectronic Systems

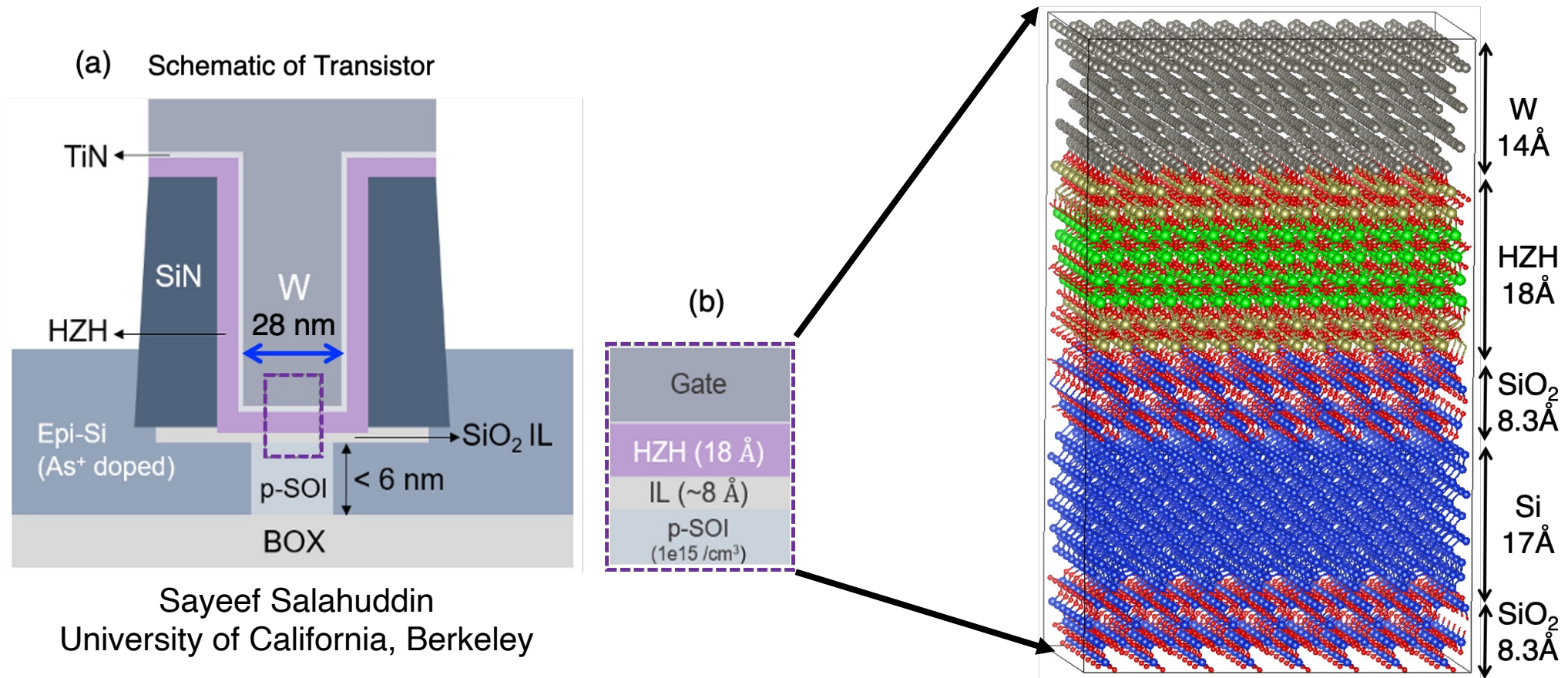


Sayeef Salahuddin
University of California, Berkeley



Bottom Up: Atomistic Model of Transistor

Fully atomistic model of channel region

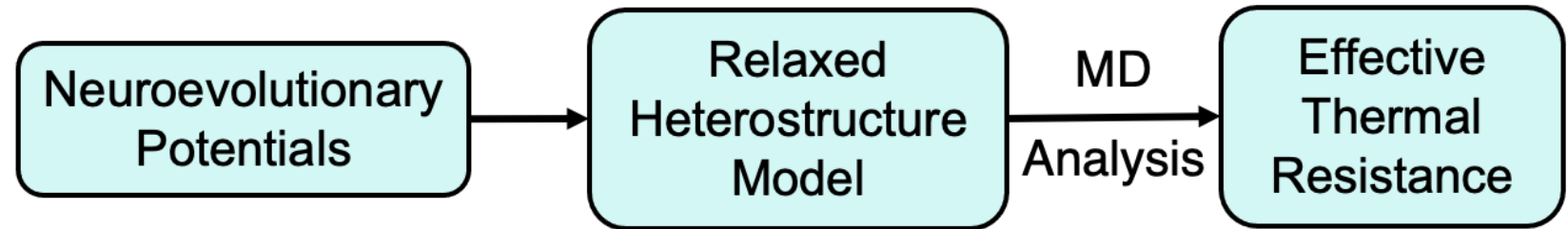
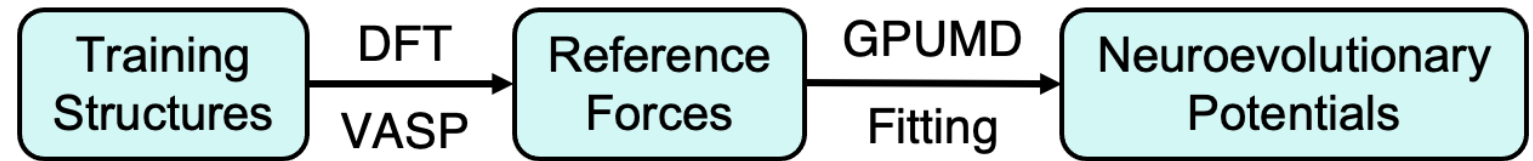
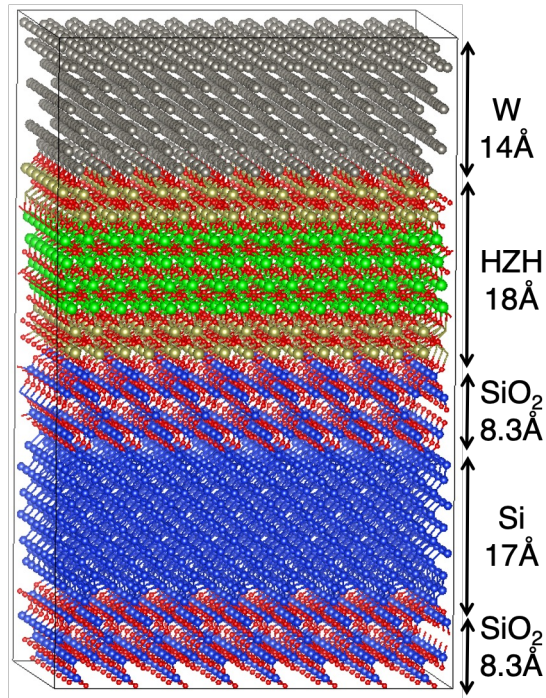


Sayeef Salahuddin
University of California, Berkeley



Bottom Up: Atomistic Model

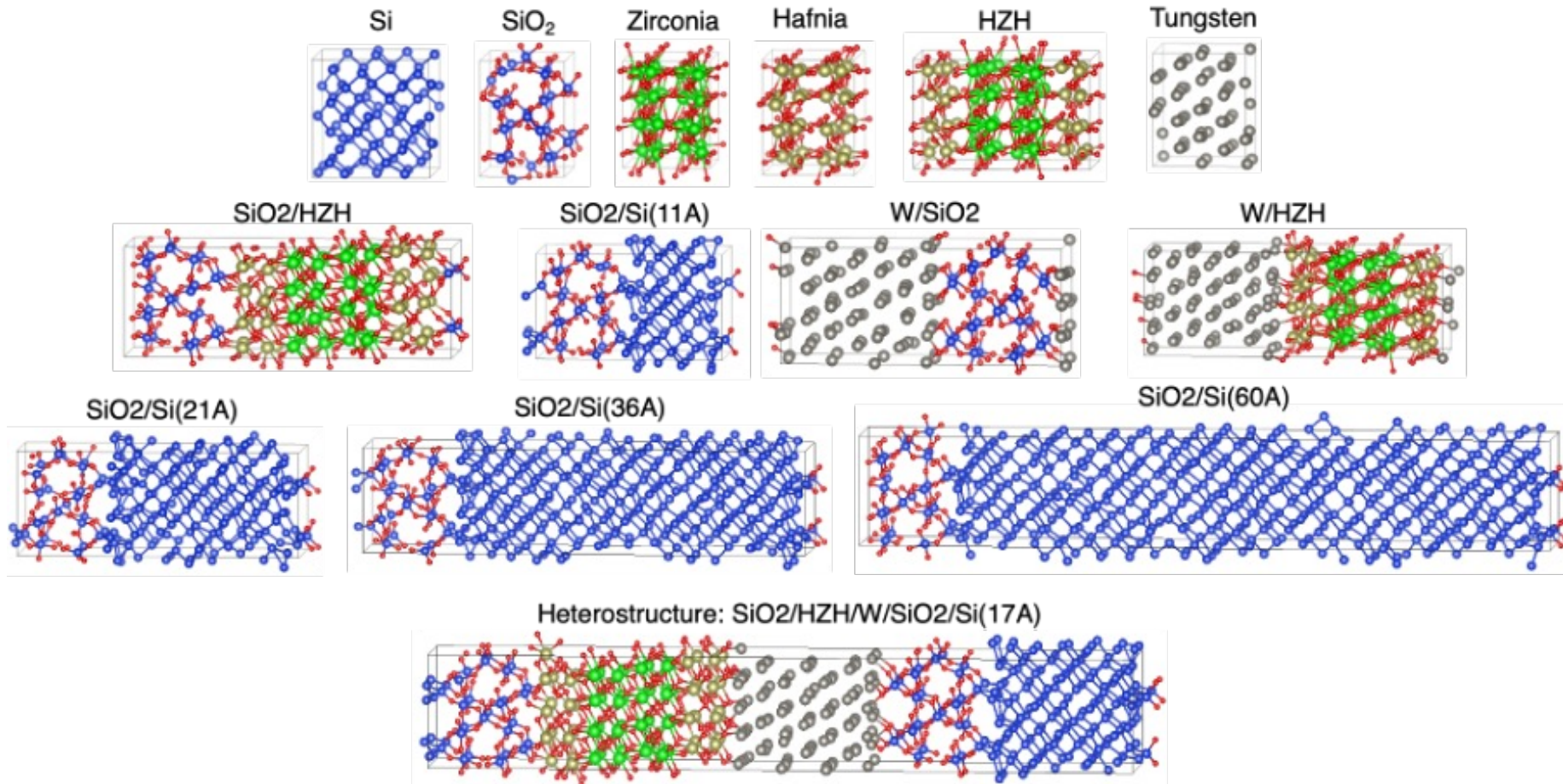
Accelerated learning of interactions using GPUs and machine learning (ML) potentials



Sanghamitra Neogi

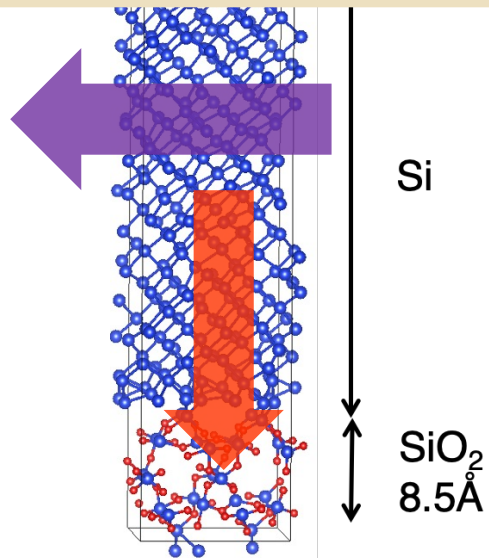
Atomistic Model: Training Data

ML-potential can capture effects due to different channel thicknesses



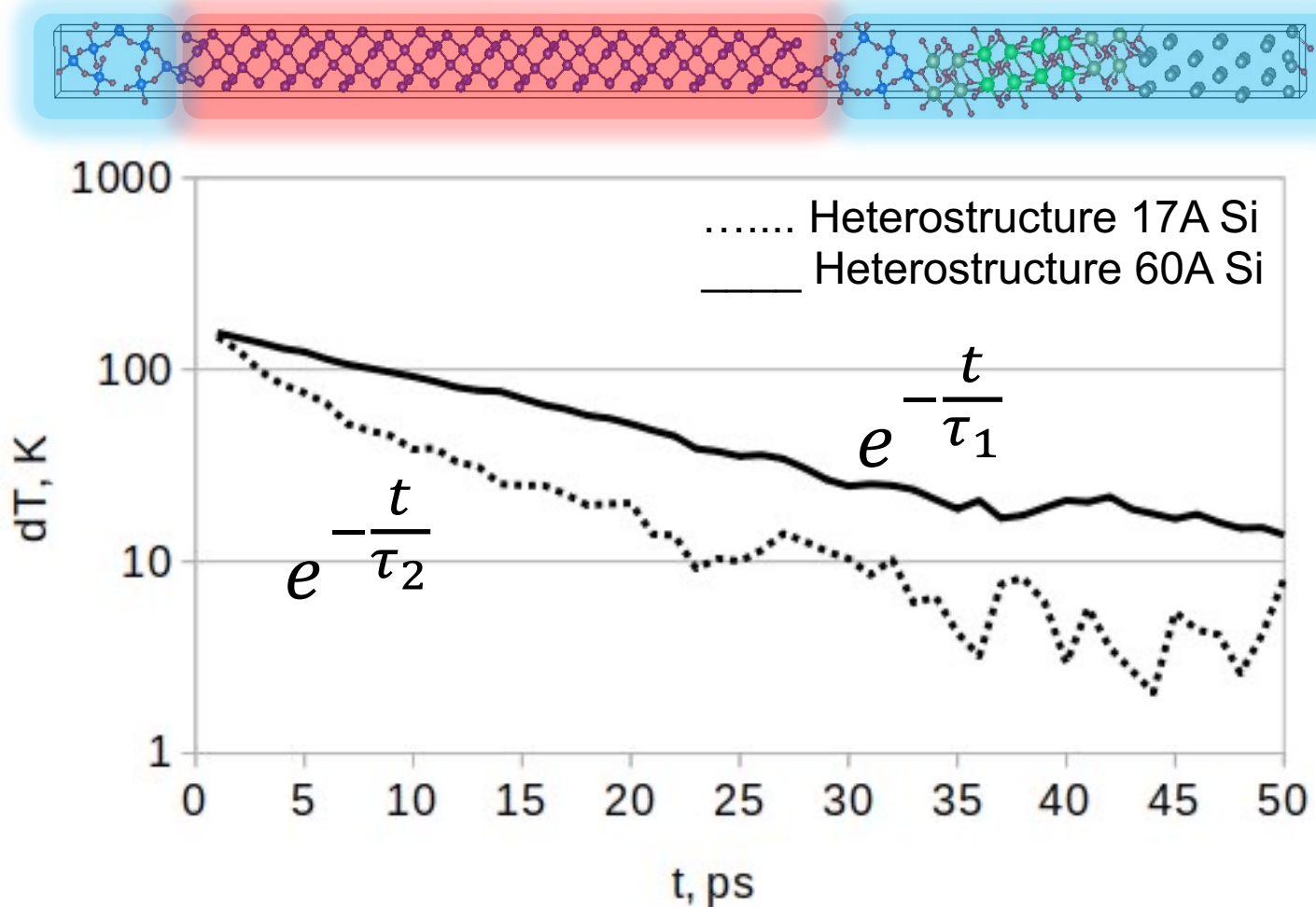
Atomistic Thermal Model: Interfaces

Prediction of thermal bottlenecks in channel region



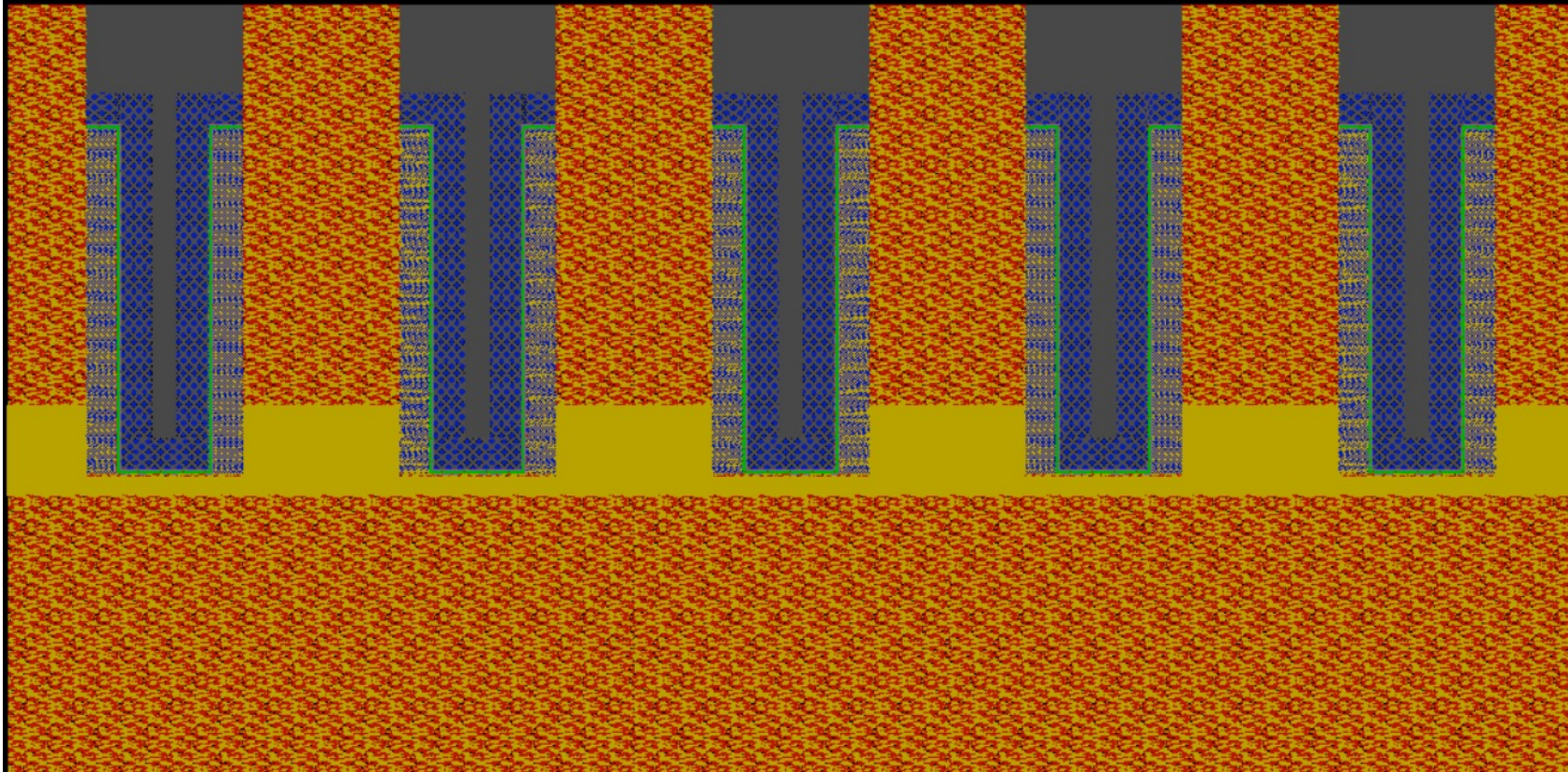
	Si(6 nm)/ SiO ₂ (0.85 nm)	Si(3.6 nm)/ SiO ₂ (0.85 nm)	Si(2.1 nm)/ SiO ₂ (0.85 nm)	Si(1.1 nm)/ SiO ₂ (0.85 nm)
Thermal conductivity (<u>cross-plane</u> , W/m-K)	2.39	1.12	0.89	0.68
Thermal conductivity (<u>in-plane</u> , W/m-K)	11.31	8.04	3.50	2.46
Interfacial conductance (GW/m ² -K)	0.768	0.535	0.645	0.751
Interfacial Resistance ($\times 10^{-9}$ m ² -K/W)	1.30	1.87	1.55	1.33

Transient Response



Time-dependent temperature decay due to different Si layer thickness

Next Step: Scaling Up



Steady-state and transient heating dynamics analysis using ML potentials and atomistic molecular dynamics

Potential roadmap extension

